STRUCTURE SEARCH

```
=> d his l31

     (FILE 'HCAPLUS' ENTERED AT 13:44:57 ON 18 MAY 2009)
L31           29 S L27 OR L30
                 SAV TEMP L31 FAN775HCP/A

=> d que stat l31
L3                STR
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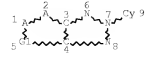

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NODE ATTRIBUTES:
DEFAULT MLEVEL IS ATOM
GGCAT   IS UNS  AT   9
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS   9

STEREO ATTRIBUTES: NONE
L4                SCR 2043
L6           2975 SEA FILE=REGISTRY SSS FUL L3 AND L4
L9           1424 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L6
L10       1225078 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  OPTIC?
L11          153 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L9 AND L10
L12               QUE  SPE=ON  ABB=ON  PLU=ON  DEVICE? OR CONTRIVANCE? OR
                   INVENTION? OR APPARAT? OR APP## OR IMPLEMENT? OR INSTR
                  UMENT? OR TOOL? OR UTENSIL? OR EQUIP?
L13       149242 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L10(2A)L12
L14           41 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L13 AND L11
L15           86 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L9 AND
                  ?LUMIN?
L16            7 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L14 AND L15
L19           57 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L9 AND
                  (REFLECT? OR TRANSMIS?)
L20           18 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L9 AND (ANOD?
                  OR CATHOD? OR ELECTROD?)
L21            3 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L19 AND L20
L22               QUE  SPE=ON  ABB=ON  PLU=ON  (CHARG? OR HOLE#  OR ELECT
                  RON# OR E)(2A)(TRANSPORT? OR MIGRAT? OR TRANSFER? OR MO
                  VE# OR MOVING# OR MOVEMENT? OR CARR?)
L23            5 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L9 AND L22
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L26               QUE  SPE=ON  ABB=ON  PLU=ON  (PY=<2004 OR PRY=<2004 OR
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L27           24 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L24 AND (L25
                  OR L26)
L28               QUE  SPE=ON  ABB=ON  PLU=ON  PHOTOELECTR? OR PHOTO?(A)E
                  LECTR?
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L30            7 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L29 AND (L25
                  OR L26)
L31           29 SEA FILE=HCAPLUS SPE=ON  ABB=ON  PLU=ON  L27 OR L30
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STRUCTURE SEARCH RESULTS

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L31 ANSWER 1 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2006:367294 HCAPLUS Full-text
DOCUMENT NUMBER: 144:413585
TITLE: Production of high quantum yield luminescent monomers, oligomers and polymers and their uses
INVENTOR(S): Morishita, Yoshii; Nomura, Satoyuki; Tsuda, Yoshihiro; Tai, Seiji; Marrocco, Matthew, L., III; Motamedi, Farshad, J.; Wang, Li-Sheng; Liang, Yongchao
PATENT ASSIGNEE(S): Hitachi Chemical Co., Ltd., Japan; Maxdem Incorporated
SOURCE: PCT Int. Appl., 168 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2006041221	A1	20060420	WO 2005-JP19352	2005 1014
			<--	
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
US 20060083945	A1	20060420	US 2004-966370	2004 1015
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JP 2008516008	T	20080515	JP 2007-516129	2005 1014
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CN 101203538	A	20080618	CN 2005-80035298	2007 0416
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KR 2007118582	A	20071217	KR 2007-710893	2007 0514
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PRIORITY APPLN. INFO.:			US 2004-966370 A	2004 1015
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			WO 2005-JP19352 W	2005 1014

OTHER SOURCE(S): MARPAT 144:413585
ED Entered STN: 21 Apr 2006
AB The invention relates generally to novel high quantum yield luminescent monomers, oligomers, and polymers, comprising benzotriazole repeating units and derivs. thereof have been discovered and utilized in optical devices and components therefor, including electroluminescent devices, light emitting devices, photoluminescent devices, organic light emitting diodes (OLEDs), OLED displays, lights, as sensors, UV stabilizers, and the like. Thus, a 1,4-dibromo-2,5-bishexyloxybenzene-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer with PL peak at 495 nm (green color) was prepared and coated on a Paytron P-coated ITO glass and followed by vapor deposited an Al film to give an EL device with high quantum yield.
IT 883741-20-5P, 1,4-Dibromo-2,5-bishexyloxybenzene-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-21-7P, 2,5-Bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-22-8P, 2,5-Bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer, SRU 883741-23-9P, 2,5-Dihexyloxy-1,4-dibromobenzene-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole copolymer 883741-28-4P, 2-(4,7-Bis(chloromethyl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol-1,4-bis(chloromethyl)-2,5-dimethoxybenzene copolymer 883741-29-5P, 1,4-Dibromo-2,5-dihexylbenzene-2,5-dihexy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-30-8P, 1,4-Dibromo-2,5-bishexyloxybenzene-2,5-dihexy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-31-9P, 2,5-Bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-1,4-dibromo-2,5-bishexyloxybenzene-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-32-0P, 2,5-Bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-1,4-dibromo-2,5-dihexylbenzene-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-33-1P, 2,6-Dibromonaphthalene-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-34-2P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-35-3P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-36-4P, 3,6-Dibromo-9-phenyl-9H-carbazole-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-37-5P, 2,4-Di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-38-6P, 2,4-Di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer, SRU 883741-39-7P, 2,7-Dibromo-9,9-dioctyl-9H-fluorene-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-

tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-40-0P, 2,5-Bis(4-bromophenyl)-1,3,4-oxadiazole-2-(4,7-bis(5-bromothiophen-2-yl)-2H-benzo[d][1,2,3]triazol-2-yl)-4,6-di-tert-butylphenol-4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester copolymer 883741-41-1P, 1,4-Dibromo-2,5-bishexyloxybenzene-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzo[d][1,2,3]triazole copolymer 883741-42-2P, 1,4-Dibromo-2,5-dihexylbenzene-2,5-dihexy-1,4-benzenebisboronic ethylene glycol ester-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzo[d][1,2,3]triazole copolymer 883741-43-3P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-44-4P, 2,7-Dibromo-9,9-dioctyl-9H-fluorene-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer
RL: DEV (Device component use); IMF (Industrial manufacture); PRP (Properties); PREP (Preparation); USES (Uses)
(production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

RN 883741-20-6 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and 1,4-dibromo-2,5-bis(hexyloxy)benzene (9CI) (CA INDEX NAME)

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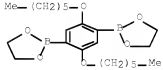
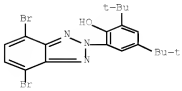
CRN 849691-48-1
CMF C22 H36 B2 O6



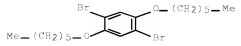
CM 2

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 3

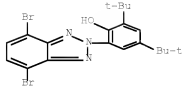
CRN 128424-36-2
CMF C18 H28 Br2 O2



RN 883741-21-7 HCAPLUS
CN Boronic acid, [2,5-bis(hexyloxy)-1,4-phenylene]bis-, polymer with 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)phenol (9CI) (CA INDEX NAME)

CM 1

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



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CRN 171089-85-3
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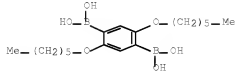
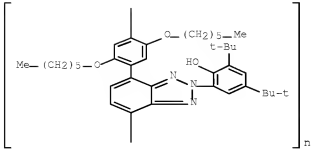


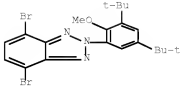
RN 883741-22-8 HCAPLUS
CN Poly[[2-[3,5-bis(1,1-dimethylethyl)-2-hydroxyphenyl]-2H-benzotriazole-4,7-diyl][2,5-bis(hexyloxy)-1,4-phenylene]] (9CI) (CA INDEX NAME)



RN 883741-23-9 HCAPLUS
CN 2H-Benzotriazole, 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-, polymer with 1,4-dibromo-2,5-bis(hexyloxy)benzene (9CI) (CA INDEX NAME)

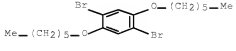
CM 1

CRN 883741-16-0
CMF C21 H25 Br2 N3 O



CM 2

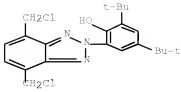
CRN 128424-36-2
CMF C18 H28 Br2 O2



RN 883741-28-4 HCAPLUS
CN Phenol, 2-[4,7-bis(chloromethyl)-2H-benzotriazol-2-yl]-4,6-bis(1,1-dimethylethyl)-, polymer with 1,4-bis(chloromethyl)-2,5-dimethoxybenzene (9CI) (CA INDEX NAME)

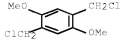
CM 1

CRN 883741-27-3
CMF C22 H27 Cl2 N3 O



CM 2

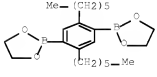
CRN 3752-97-4
CMF C10 H12 Cl2 O2



RN 883741-29-5 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 1,4-dibromo-2,5-dihexylbenzene and 2,2'-(2,5-dihexyl-1,4-phenylene)bis[1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

CM 1

CRN 883741-17-1
CMF C22 H36 B2 O4



CM 2

CRN 784163-33-3
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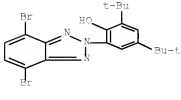
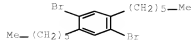


CM 3

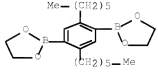
CRN 117635-21-9
CMF C18 H28 Br2



RN 883741-30-8 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 1,4-dibromo-2,5-bis(hexyloxy)benzene and 1,4-dibromo-2,5-bis(hexyloxy)-1,3,2-dioxaborolane (9CI) (CA INDEX NAME)

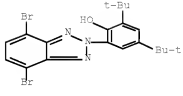
CM 1

CRN 883741-17-1
CMF C22 H36 B2 O4



CM 2

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 3

CRN 128424-36-2
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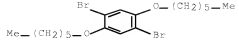
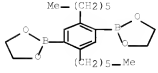


RN 883741-31-9 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane], 1,4-dibromo-2,5-bis(hexyloxy)benzene and 2,2'-(2,5-dihexyl-1,4-phenylene)bis[1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

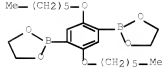
CM 1

CRN 883741-17-1
CMF C22 H36 B2 O4



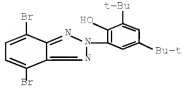
CM 2

CRN 849691-48-1
CMF C22 H36 B2 O6



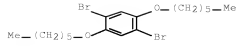
CM 3

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 4

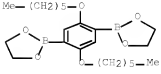
CRN 128424-36-2
CMF C18 H28 Br2 O2



RN 883741-32-0 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and 1,4-dibromo-2,5-dihexylbenzene (9CI) (CA INDEX NAME)

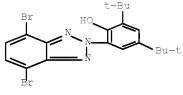
CM 1

CRN 849691-48-1
CMF C22 H36 B2 O6



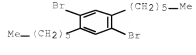
CM 2

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 3

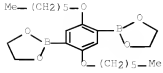
CRN 117635-21-9
CMF C18 H28 Br2



RN 883741-33-1 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and 2,6-dibromonaphthalene (9CI) (CA INDEX NAME)

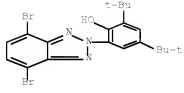
CM 1

CRN 849691-48-1
CMF C22 H36 B2 O6



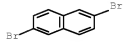
CM 2

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 3

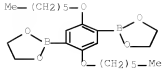
CRN 13720-06-4
CMF C10 H6 Br2



RN 883741-34-2 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and 4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine (9CI) (CA INDEX NAME)

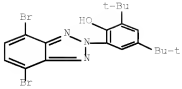
CM 1

CRN 849691-48-1
CMF C22 H36 B2 O6



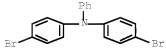
CM 2

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 3

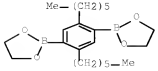
CRN 81090-53-1
CMF C18 H13 Br2 N



RN 883741-35-3 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine and 2,2'-(2,5-dihexyl-1,4-phenylene)bis[1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

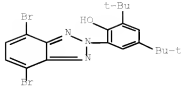
CM 1

CRN 883741-17-1
CMF C22 H36 B2 O4



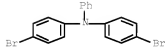
CM 2

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 3

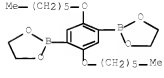
CRN 81090-53-1
CMF C18 H13 Br2 N



RN 883741-36-4 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and 3,6-dibromo-9-phenyl-9H-carbazole (9CI) (CA INDEX NAME)

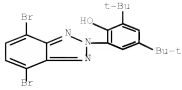
CM 1

CRN 849691-48-1
CMF C22 H36 B2 O6



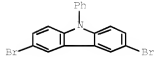
CM 2

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 3

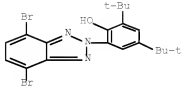
CRN 57103-20-5
CMF C18 H11 Br2 N



RN 883741-37-5 HCAPLUS
CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,2'-(9,9-dioctyl-9H-fluorene-2,7-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

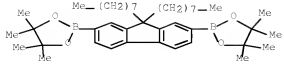
CM 1

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



CM 2

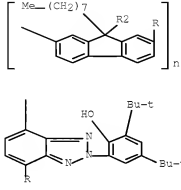
CRN 196207-58-6
CMF C41 H64 B2 O4



RN 883741-38-6 HCAPLUS

CN Poly[[2-[3,5-bis(1,1-dimethylethyl)-2-hydroxyphenyl]-2H-benzotriazole-4,7-diyl](9,9-dioctyl-9H-fluorene-2,7-diyl)] (9CI) (CA INDEX NAME)

PAGE 1-A



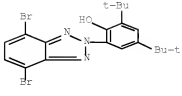
PAGE 2-A

RN 883741-39-7 HCAPLUS

CN Phenol, 2-(4,7-dibromo-2H-benzotriazol-2-yl)-4,6-bis(1,1-dimethylethyl)-, polymer with 2,7-dibromo-9,9-dioctyl-9H-fluorene and 2,2'-(9,9-dioctyl-9H-fluorene-2,7-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

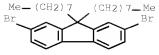
CM 1

CRN 784163-33-3
CMF C20 H23 Br2 N3 O



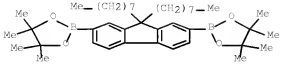
CM 2

CRN 198964-46-4
CMF C29 H40 Br2



CM 3

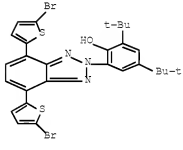
CRN 196207-58-6
CMF C41 H64 B2 O4



RN 883741-40-0 HCAPLUS
CN Phenol, 2-[4,7-bis(5-bromo-2-thienyl)-2H-benzotriazol-2-yl]-4,6-bis(1,1-dimethylethyl)-, polymer with 2,5-bis(4-bromophenyl)-1,3,4-oxadiazole, 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and 4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine (9CI) (CA INDEX NAME)

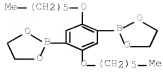
CM 1

CRN 883741-19-3
CMF C28 H27 Br2 N3 O S2



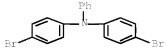
CM 2

CRN 849691-48-1
CMF C22 H36 B2 O6



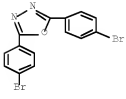
CM 3

CRN 81090-53-1
CMF C18 H13 Br2 N



CM 4

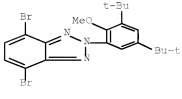
CRN 19542-05-3
CMF C14 H8 Br2 N2 O



RN 883741-41-1 HCAPLUS
CN 2H-Benzotriazole, 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-, polymer with 2,2'-[2,5-bis(hexyloxy)-1,4-phenylene]bis[1,3,2-dioxaborolane] and 1,4-dibromo-2,5-bis(hexyloxy)benzene (9CI) (CA INDEX NAME)

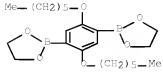
CM 1

CRN 883741-16-0
CMF C21 H25 Br2 N3 O



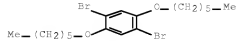
CM 2

CRN 849691-48-1
CMF C22 H36 B2 O6



CM 3

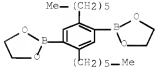
CRN 128424-36-2
CMF C18 H28 Br2 O2



RN 883741-42-2 HCAPLUS
CN 2H-Benzotriazole, 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-, polymer with 1,4-dibromo-2,5-dihexylbenzene and (2,5-dihexyl-1,4-phenylene)-1,3,2-dioxaborolane (9CI) (CA INDEX NAME)

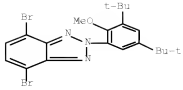
CM 1

CRN 883741-17-1
CMF C22 H36 B2 O4



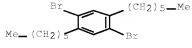
CM 2

CRN 883741-16-0
CMF C21 H25 Br2 N3 O



CM 3

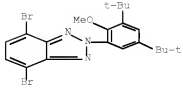
CRN 117635-21-9
CMF C18 H28 Br2



RN 883741-43-3 HCAPLUS
CN Benzenamine, 4-bromo-N-(4-bromophenyl)-N-phenyl-, polymer with 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-2H-benzotriazole and 2,2'-(9,9-dioctyl-9H-fluorene-2,7-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

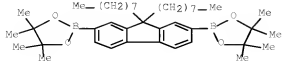
CM 1

CRN 883741-16-0
CMF C21 H25 Br2 N3 O



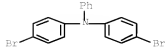
CM 2

CRN 196207-58-6
CMF C41 H64 B2 O4



CM 3

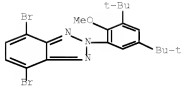
CRN 81090-53-1
CMF C18 H13 Br2 N



RN 883741-44-4 HCAPLUS
CN 2H-Benzotriazole, 2-[3,5-bis(1,1-dimethylethyl)-2-methoxyphenyl]-4,7-dibromo-, polymer with 2,7-dibromo-9,9-dioctyl-9H-fluorene and 2,2'-(9,9-dioctyl-9H-fluorene-2,7-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

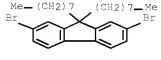
CM 1

CRN 883741-16-0
CMF C21 H25 Br2 N3 O



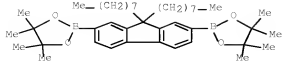
CM 2

CRN 198964-46-4
CMF C29 H40 Br2



CM 3

CRN 196207-58-6
CMF C41 H64 B2 O4



CC 37-3 (Plastics Manufacture and Processing)
Section cross-reference(s): 35, 74
ST benzotriazole luminescent monomer oligomer polymer electroluminescent device
IT Electroluminescent devices
Luminescent substances
Sensors
(production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)
IT 883741-48-8P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(chemical sensor; production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)
IT 9003-53-6D, sulfonated
RL: DEV (Device component use); USES (Uses)
(dopant for PEDOT; production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)
IT 126213-51-2
RL: DEV (Device component use); USES (Uses)
(doped with PSS; production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)
IT 2835-58-7P, 2-Phenylazoaniline 69272-50-0P, 3,6-Dibromo-1,2-phenylenediamine 883741-18-2P, 2,4-Di-tert-butyl-6-(4,7-di(thiophen-2-yl)-2H-benzotriazol-2-yl)phenol
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(intermediate; production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)
IT 1916-72-9P, 2-Phenyl-2H-benzotriazole
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(intermediate; production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)
IT 57103-20-5P, 3,6-Dibromo-9-phenylcarbazole 81090-53-1P, 4,4'-Dibromotriphenylamine 128424-36-2P, 2,5-Dihexyloxy-1,4-dibromobenzene 784163-33-3P, 2,4-Di-tert-butyl-6-(4,7-dibromo-2H-benzo[d][1,2,3]triazol-2-yl)phenol 849691-48-1P 851106-87-1P 883741-16-0P, 2-(3,5-Di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole 883741-17-1P 883741-19-3P, 2-(4,7-Bis(5-bromothiophen-2-yl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol 883741-55-7P, 2-(3,5-Di-tert-butyl-2-methoxyphenyl)-4,6-dibromo-2H-benzotriazole 883741-56-8P, 2-(3,5-Di-tert-butyl-2-methoxyphenyl)-5,6-dibromo-2H-benzotriazole
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(monomer; production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)
IT 883741-51-3, 4,6-Dibromo-2-hexyl-2H-benzotriazole 883741-52-4, 5,6-Dibromo-2-hexyl-2H-benzotriazole 883741-53-5, 2,4-Di-tert-butyl-6-(4,6-dibromo-2H-benzo[d][1,2,3]triazol-2-yl)phenol 883741-54-6, 2,4-Di-tert-butyl-6-(5,6-dibromo-2H-benzo[d][1,2,3]triazol-2-yl)phenol
RL: RCT (Reactant); RACT (Reactant or reagent)

(monomer; production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

IT 1044764-63-7, Baytron P
RL: DEV (Device component use); USES (Uses)
(production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

IT 883741-20-6P, 1,4-Dibromo-2,5-bishexyloxybenzene-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-21-7P, 2,5-Bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-22-8P, 2,5-Bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer, SRU 883741-23-9P, 2,5-Dihexyloxy-1,4-dibromobenzene-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole copolymer 883741-28-4P, 2-(4,7-Bis(chloromethyl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol-1,4-bis(chloromethyl)-2,5-dimethoxybenzene copolymer 883741-29-5P, 1,4-Dibromo-2,5-dihexylbenzene-2,5-dihexy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-30-8P, 1,4-Dibromo-2,5-bishexyloxybenzene-2,5-dihexy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-31-9P, 2,5-Bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-1,4-dibromo-2,5-bishexyloxybenzene-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-32-0P, 2,5-Bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-1,4-dibromo-2,5-dihexylbenzene-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-33-1P, 2,6-Dibromonaphthalene-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-34-2P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-35-3P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-dihexyl-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-36-4P, 3,6-Dibromo-9-phenyl-9H-carbazole-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol copolymer 883741-37-5P, 2,4-Di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-38-6P, 2,4-Di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer, SRU 883741-39-7P, 2,7-Dibromo-9,9-dioctyl-9H-fluorene-2,4-di-tert-butyl-6-(4,7-dibromobenzotriazol-2-yl)-phenol-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-40-0P, 2,5-Bis(4-bromophenyl)-1,3,4-oxadiazole-2-(4,7-bis(5-bromothiophen-2-yl)-2H-benzo[d][1,2,3]triazol-2-yl)-4,6-di-tert-butylphenol-4-bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bishexyloxy-1,4-

benzenebisboronic ethylene glycol ester copolymer
883741-41-1P, 1,4-Dibromo-2,5-bishexyloxybenzene-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzo[d][1,2,3]triazole copolymer 883741-42-2P, 1,4-Dibromo-2,5-dihexylbenzene-2,5-dihexy-1,4-benzenebisboronic ethylene glycol ester-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzo[d][1,2,3]triazole copolymer 883741-43-3P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-44-4P, 2,7-Dibromo-9,9-dioctyl-9H-fluorene-2-(3,5-di-tert-butyl-2-methoxyphenyl)-4,7-dibromo-2H-benzotriazole-4,4,5,5-tetramethyl-2-(2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dioctyl-9H-fluoren-7-yl)-1,3,2-dioxaborolane copolymer 883741-45-5P, 1,4-Dibromo-2,5-bishexyloxybenzene-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-4,7-dibromo-2-hexyl-2H-benzotriazole copolymer 883741-46-6P, 1,4-Dibromo-2,5-bishexyloxybenzene-2,5-dihexy-1,4-benzenebisboronic ethylene glycol ester-4,7-dibromo-2-hexyl-2H-benzotriazole copolymer 883741-47-7P, 4-Bromo-N-(4-bromophenyl)-N-phenylbenzenamine-2,5-bishexyloxy-1,4-benzenebisboronic ethylene glycol ester-4,7-dibromo-2-hexyl-2H-benzotriazole copolymer
RL: DEV (Device component use); IMF (Industrial manufacture); PRP (Properties); PREP (Preparation); USES (Uses)
(production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

IT 16292-17-4P, 4,4'-Dibromodiphenylamine 67399-93-3P, 1,4-Dihexyloxybenzene 171089-85-3P 883741-24-0P, 2-(4,7-Bis(4-(dimethylamino)phenyl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol 883741-25-1P 883741-27-3P, 2-(4,7-Bis(chloromethyl)-2H-benzotriazol-2-yl)-4,6-di-tert-butylphenol 883741-49-9P 883741-50-2P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

IT 74-88-4, reactions 95-14-7, 1H-Benzotriazole 95-54-5, 1,2-Phenylenediamine, reactions 98-80-6, Phenylboronic acid 98-95-3, Nitrobenzene, reactions 107-21-1, Ethylene glycol, reactions 111-25-1, 1-Bromohexane 121-43-7, Trimethyl borate 122-39-4, reactions 123-31-9, p-Hydroquinone, reactions 128-08-5, N-Bromosuccinimide 542-88-1, Bis(chloromethyl)ether 591-50-4, Iodobenzene 814-49-3, Diethyl phosphochloridate 1150-62-5, 9-Phenylcarbazole 2440-22-4, Tinuvin P 3240-34-4, Iodobenzene diacetate 3846-71-7 7726-95-6, Bromine, reactions 10035-10-6, Hydrogenbromide, reactions 15155-41-6, 4,7-Dibromobenzo[1,2,5]thiadiazole 28611-39-4, 4-(Dimethylamino)phenylboronic acid 54663-78-4, Tributyl(thiophen-2-yl)stannate 131117-66-3, 2,5-Dihexyl-1,4-benzenediboronic acid
RL: RCT (Reactant); RACT (Reactant or reagent)
(production of high quantum yield luminescent monomers, oligomers and polymers for electroluminescent devices)

REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L31 ANSWER 2 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2006:50852 HCAPLUS Full-text
DOCUMENT NUMBER: 144:138888
TITLE: Manufacture of aromatic polycarbonates as

	binders for electrophotographic photoconductors showing good abrasion resistance and low surface energy
INVENTOR(S):	Li, Hung Guo; Nagai, Kazukiyo; Okuda, Harukazu; Hatanaka, Masahide
PATENT ASSIGNEE(S):	Ricoh Co., Ltd., Japan; Nisshin Chemical Industry Co., Ltd.
SOURCE:	Jpn. Kokai Tokkyo Koho, 35 pp. CODEN: JKXXAF
DOCUMENT TYPE:	Patent
LANGUAGE:	Japanese
FAMILY ACC. NUM. COUNT:	1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006016566	A	20060119	JP 2004-197925	2004 0705 <--
PRIORITY APPLN. INFO.:			JP 2004-197925	2004 0705 <--

ED Entered STN: 19 Jan 2006

AB The polycarbonates are manufactured by solution polymerization of HOXOH (X = bivalent aliphatic group, bivalent alicyclic group, bivalent aromatic group, etc.) with OH-containing acrylic polyorganosiloxanes and carbonyl halides. Preferably, the polyorganosiloxanes are manufactured by grafting acrylic monomers containing 3-(N-benzotriazole)-4-hydroxyphenethyl methacrylate onto silicones. Electrophotog. process and apparatus, and process cartridges are also claimed.

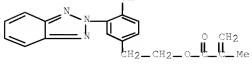
IT 873545-93-8P
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)

RN 873545-93-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with 4,4'-cyclohexylidenebis[phenol], ethenyldimethoxymethylsilane, 1,1,1,3,3,3-hexachloro-2-propanone, methyl 2-methyl-2-propenoate, octamethylcyclotetrasiloxane and (2,4,6-trioxo-1,3,5-triazine-1,3,5(2H,4H,6H)-triyl)tri-2,1-ethanediyl tri-2-propenoate (9CI) (CA INDEX NAME)

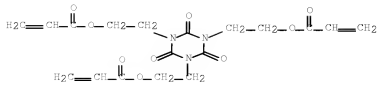
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



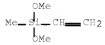
CM 2

CRN 40220-08-4
CMF C18 H21 N3 O9



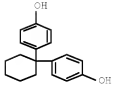
CM 3

CRN 16753-62-1
CMF C5 H12 O2 Si



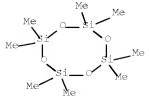
CM 4

CRN 843-55-0
CMF C18 H20 O2



CM 5

CRN 556-67-2
CMF C8 H24 O4 Si4



CM 6

CRN 116-16-5
CMF C3 Cl6 O

CM 7

CRN 80-62-6
CMF C5 H8 O2

CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
ST acrylic polysiloxane arom polycarbonate electrophotog photoconductor abrasion resistance; benzotriazole hydroxyphenethyl methacrylate polysiloxane polycarbonate electrophotog photoconductor; soln polymn graft acrylic polysiloxane carbonyl halide
IT Abrasion-resistant materials
Electrophotographic photoconductors
(photoreceptors)
(manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)
IT Polysiloxanes, preparation
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(polycarbonate-polyisocyanurate-, acrylic; manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy)
IT Polyisocyanurates
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(polycarbonate-polysiloxane-, acrylic; manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy)
IT Polycarbonates, preparation
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(polyisocyanurate-polysiloxane-, acrylic; manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy)
IT Polymerization
(solution; manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good

abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)

IT 873545-93-8P
RL: DEV (Device component use); IMF (Industrial manufacture); PREP (Preparation); USES (Uses)
(manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)

IT 110-86-1, Pyridine, reactions
RL: RGT (Reagent); RACT (Reactant or reagent)
(manufacture of aromatic polycarbonates as binders for electrophotog. photoconductors showing good abrasion resistance and low surface energy by solution polymerization of dihydroxy compds. with OH-containing acrylic polyorganosiloxanes and carbonyl halides)

L31 ANSWER 3 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2005:1176034 HCAPLUS Full-text
DOCUMENT NUMBER: 143:442130
TITLE: Anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment
INVENTOR(S): Aoki, Kenji; Fujita, Mitsuhiro; Hiraki, Tadayoshi
PATENT ASSIGNEE(S): Kansai Paint Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005307161	A	20051104	JP 2004-359536	20041213
			<--	
CN 1673295	A	20050928	CN 2005-10053994	20050315
			<--	
PRIORITY APPLN. INFO.:			JP 2004-82735 A	20040322
			<--	
			JP 2004-359536 A	20041213
			<--	

ED Entered STN: 06 Nov 2005
AB Title coatings comprise (A) core-shell emulsion obtained by multi-step emulsion polymerization of polymerizable unsatd. monomers in the presence of water and emulsifiers, (B) acrylic resins, and (C) crosslinkers, wherein the core-shell emulsion contain 1-40% alkoxysilyl-containing monomer units and is prepared by (i) first radical emulsion polymerization of alkoxysilyl-containing radically polymerizable monomers, ≥1 radically polymerizable unsatd. monomer selected from UV-absorbing component-containing monomers, light stabilizing component-containing monomers, and fluoro-containing monomers, copolymerizable monomers, and optionally monomers having ≥2 radically polymerizable groups, and second emulsion polymerization of alkoxysilyl-containing radically polymerizable monomers, copolymerizable monomers, and optionally monomers having ≥2 radically polymerizable groups. Thus, Adeka Reasoap SE 10N 1, styrene 20, Bu

acrylate 17, 2-hydroxyethyl acrylate 2, 1,6-hexanediol diacrylate 5, KBM 503 4, and Ruva 93 2 parts were emulsion-polymerized, Adeka Reasoap SE 10N 1, styrene 15, Bu acrylate 13, 2-hydroxyethyl acrylate 4, 1,6-hexanediol diacrylate 3, and KBM 503 15 parts were added therein and polymerized to give 20%-solids core-shell copolymer with particle diameter 127 nm, 15 parts of which was mixed with 45 parts 60%-solids styrene-Me methacrylate-Bu acrylate-Et acrylate-2-hydroxyethyl acrylate-acrylic acid copolymer solution, 40 parts Nikalac MX 430, 0.4 equiv (based on OH group) triethylamine, and water, adjusted pH at 8.2 and solid content 10% to give an anionic electrodeposition coating, showing good stability, weather resistance, and dice mark concealment, pencil hardness (crosslinked) 4 H, and 60° gloss 16.

IT 868663-68-7P 868663-72-3P 868681-86-1P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

RN 868663-68-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate, formaldehyde, 1,6-hexanediyl di-2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 2-propenoic acid, α-sulfo-ω-[1-[(nonylphenoxy)methyl]-2-(2-propenyloxy)ethoxy]poly(oxy-1,2-ethanediyl) ammonium salt, 1,3,5-triazine-2,4,6-triamine and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI) (CA INDEX NAME)

CM 1

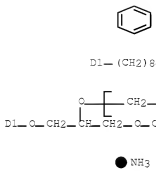
CRN 121-44-8
CMF C6 H15 N

CM 2

CRN 868663-67-6
CMF (C18 H17 N3 O3 . C12 H18 O4 . C10 H20 O5 Si . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H6 N6 . C3 H4 O2 . (C2 H4 O)n C21 H34 O6 S . C H2 O . H3 N)x
CCI PMS

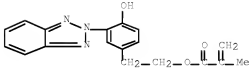
CM 3

CRN 113405-85-9
CMF (C2 H4 O)n C21 H34 O6 S . H3 N
CCI IDS, PMS



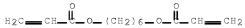
CM 4

CRN 96478-09-0
CMF C18 H17 N3 O3



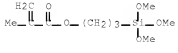
CM 5

CRN 13048-33-4
CMF C12 H18 O4



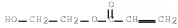
CM 6

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 7

CRN 818-61-1
CMF C5 H8 O3

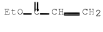


CM 8

CRN 141-32-2
CMF C7 H12 O2

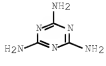
CM 9

CRN 140-88-5
CMF C5 H8 O2



CM 10

CRN 108-78-1
CMF C3 H6 N6



CM 11

CRN 100-42-5
CMF C8 H8

CM 12

CRN 80-62-6

CMF C5 H8 O2

CM 13

CRN 79-10-7
CMF C3 H4 O2

CM 14

CRN 50-00-0
CMF C H2 O

RN 868663-72-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
formaldehyde, 1,6-hexanediyl di-2-propenoate, 2-hydroxyethyl
2-propenoate, methyl 2-methyl-2-propenoate,
1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate,
2-propenoic acid, α-sulfo-ω-[1-[(nonylphenoxy)methyl]-
2-(2-propenyloxy)ethoxy]poly(oxy-1,2-ethanediyl) ammonium salt,
1,3,5-triazine-2,4,6-triamine and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
(CA INDEX NAME)

CM 1

CRN 121-44-8
CMF C6 H15 N

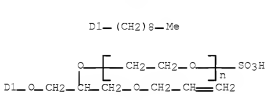
CM 2

CRN 868663-71-2
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C12 H18 O4 . C10 H20 O5 Si .
C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H6 N6

. C3 H4 O2 . (C2 H4 O)n C21 H34 O6 S . C H2 O . H3 N)x
CCI PMS

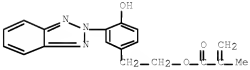
CM 3

CRN 113405-85-9
CMF (C2 H4 O)n C21 H34 O6 S . H3 N
CCI IDS, PMS



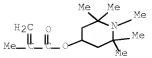
CM 4

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 5

CRN 68548-08-3
CMF C14 H25 N O2

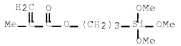


CM 6

CRN 13048-33-4
CMF C12 H18 O4

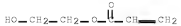
CM 7

CRN 2530-85-0
CMF C10 H20 O5 Si



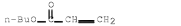
CM 8

CRN 818-61-1
CMF C5 H8 O3



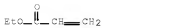
CM 9

CRN 141-32-2
CMF C7 H12 O2



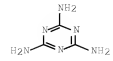
CM 10

CRN 140-88-5
CMF C5 H8 O2



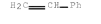
CM 11

CRN 108-78-1
CMF C3 H6 N6



CM 12

CRN 100-42-5
CMF C8 H8



CM 13

CRN 80-62-6
CMF C5 H8 O2

CM 14

CRN 79-10-7
CMF C3 H4 O2

CM 15

CRN 50-00-0
CMF C H2 O

RN 868681-86-1 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, Duranate TPA-B 80, ethenylbenzene, ethyl
2-propenoate, formaldehyde, 1,6-hexanediyl di-2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,

2-propenoic acid, α-sulfo-ω-[1-[(nonylphenoxy)methyl]-
2-(2-propenyloxy)ethoxy]poly(oxy-1,2-ethanediyl) ammonium salt,
1,3,5-triazine-2,4,6-triamine and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
(CA INDEX NAME)

CM 1

CRN 121-44-8
CMF C6 H15 N

CM 2

CRN 868681-85-0
CMF (C18 H17 N3 O3 . C12 H18 O4 . C10 H20 O5 Si . C8 H8 . C7 H12
O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H6 N6 . C3 H4 O2 .
(C2 H4 O)n C21 H34 O6 S . C H2 O . H3 N . Unspecified)x
CCI PMS

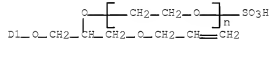
CM 3

CRN 178359-56-3
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

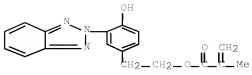
CM 4

CRN 113405-85-9
CMF (C2 H4 O)n C21 H34 O6 S . H3 N
CCI IDS, PMS



CM 5

CRN 96478-09-0
CMF C18 H17 N3 O3

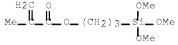


CM 6

CRN 13048-33-4
CMF C12 H18 O4

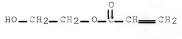
CM 7

CRN 2530-85-0
CMF C10 H20 O5 Si



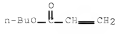
CM 8

CRN 818-61-1
CMF C5 H8 O3



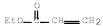
CM 9

CRN 141-32-2
CMF C7 H12 O2



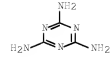
CM 10

CRN 140-88-5
CMF C5 H8 O2



CM 11

CRN 108-78-1
CMF C3 H6 N6



CM 12

CRN 100-42-5
CMF C8 H8

CM 13

CRN 80-62-6
CMF C5 H8 O2

CM 14

CRN 79-10-7
CMF C3 H4 O2

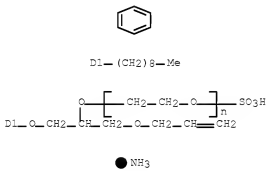
CM 15

CRN 50-00-0
CMF C H2 O

IT 868663-64-3P 868663-65-4P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(core-shell, prepolymer; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)
RN 868663-64-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, 1,6-hexanediyl di-2-propenoate, 2-hydroxyethyl 2-propenoate, α-sulfo-ω-[1-[(nonylphenoxy)methyl]-2-(2-propenyloxy)ethoxy][poly(oxy-1,2-ethanediyl)] ammonium salt and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

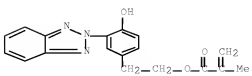
CM 1

CRN 113405-85-9
CMF (C2 H4 O)n C21 H34 O6 S . H3 N
CCI IDS, PMS



CM 2

CRN 96478-09-0
CMF C18 H17 N3 O3

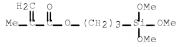


CM 3

CRN 13048-33-4
CMF C12 H18 O4

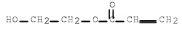
CM 4

CRN 2530-85-0
CMF C10 H20 O5 Si



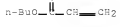
CM 5

CRN 818-61-1
CMF C5 H8 O3



CM 6

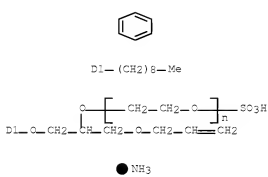
CRN 141-32-2
CMF C7 H12 O2



RN 868663-65-4 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, 1,6-hexanediyl di-2-propenoate,
2-hydroxyethyl 2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl
2-methyl-2-propenoate, α-sulfo-ω-[1-
[(nonylphenoxy)methyl]-2-(2-propenyloxy)ethoxy][poly(oxy-1,2-
ethanediyl)] ammonium salt and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

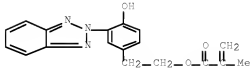
CM 1

CRN 113405-85-9
CMF (C2 H4 O)n C21 H34 O6 S . H3 N
CCI IDS, PMS



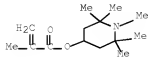
CM 2

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 3

CRN 68548-08-3
CMF C14 H25 N O2

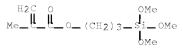


CM 4

CRN 13048-33-4
CMF C12 H18 O4

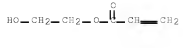
CM 5

CRN 2530-85-0
CMF C10 H20 O5 Si



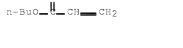
CM 6

CRN 818-61-1
CMF C5 H8 O3



CM 7

CRN 141-32-2
CMF C7 H12 O2



IC ICM C09D151-00
ICS C08F275-00; C09D005-02; C09D005-32; C09D005-44; C09D133-00
CC 42-10 (Coatings, Inks, and Related Products)
ST anionic ~~electrodepcsition~~ coating weather resistance stability dice mark concealment; hydroxy contg acrylic polyoxyalkylene core shell Nikalac copolymer coating
IT Polyoxyalkylenes, preparation
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(acrylic, core-shell, prepolymer; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
IT Polyoxyalkylenes, preparation
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(acrylic, fluorine-containing, core-shell, prepolymer; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)
IT Aminoplasts
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic, polyoxyalkylene-; anionic ~~electrodeposition~~ coatings with good weather resistance, stability, and dice mark concealment)

IT Polyoxyalkylenes, uses
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic-aminoplast-, fluorine-containing; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT Fluoropolymers, uses
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic-aminoplast-polyoxyalkylene-; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT Fluoropolymers, preparation
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(acrylic-polyoxyalkylene-, core-shell, prepolymer; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT Aminoplasts
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic-polyoxyalkylene-, fluorine-containing; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT Coating materials
(electrodeposition; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT Coating materials
(weather-resistant; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT 868663-68-7P 868663-72-3P 868663-77-8P
868681-86-1P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT 868663-70-1P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT 868663-64-3P 868663-65-4P 868663-66-5P
868681-84-9P, Adeka Reasoap SE 10N-butyl acrylate-Fancryl FA 711MM-1,6-hexanediol diacrylate-2-hydroxyethyl acrylate-KBM 503 copolymer
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(core-shell, prepolymer; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

IT 105524-01-4P, Acrylic acid-butyl acrylate-ethyl acrylate-2-hydroxyethyl acrylate-methyl methacrylate-styrene copolymer triethylamine salt
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(prepolymer; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

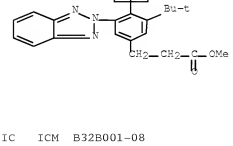
IT 7429-90-5D, Aluminum, oxidized
RL: TEM (Technical or engineered material use); USES (Uses)
(substrate; anionic electrodeposition coatings with good weather resistance, stability, and dice mark concealment)

L31 ANSWER 4 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2004:1059254 HCAPLUS Full-text
DOCUMENT NUMBER: 142:45858

TITLE: Electrophotographic photoconductor and process for its manufacturing
INVENTOR(S): Rogge, Peter R.; Weidert, Edward
PATENT ASSIGNEE(S): Circular Technologies, USA
SOURCE: PCT Int. Appl., 30 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2004106051	A1	20041209	WO 2003-US17629	20030527
			<--	
WO 2004106051	A8	20060323		
W: US				
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR				
PRIORITY APPLN. INFO.:			WO 2003-US17629	20030527
			<--	

ED Entered STN: 10 Dec 2004
AB An electrophotog. photoconductor for use in electrophotog. applications is provided. The electrophotog. photoconductor is comprised of a monolithic elastic material layer comprised of at least a polyol, a polyisocyanate, and a hydroxyl-containing acrylate monomer, and addnl. optionally comprised of some combination of a conductive additive, an UV absorber, and a photoinitiator, that is deposited on an electroconductive substrate. The elastic material later is then exposed to UV light, thereby creating an elec. semi-conductive surface layer. An electrophotog. photoconductor prepared in this fashion has a hardness of 5-50 Shore A durometer, a surface resistivity of 105-1012 Ohms/cm2 and a volume resistivity of 104-101° Ohms-cm.
IT 136457-10-8, Tinuvin 213
RL: TEM (Technical or engineered material use); USES (Uses)
(electrophotog. photoconductor and process for its manufacturing)
RN 136457-10-8 HCAPLUS
CN Poly(oxy-1,2-ethanediyl), α-[2-(2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-(3-methoxy-3-oxopropyl)phenyl]-ω-hydroxy- (CA INDEX NAME)



IC ICM B32B001-08
ICS B32B025-00; B32B031-28; C08F002-48; C08F002-50; C08J007-04; G03G015-02
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST electrophotog photoconductor manuf

IT Electrophotographic photoconductors (photoreceptors)
(electrophotog. photoconductor and process for its manufacturing)
IT 25736-86-1, Polyethylene glycol monomethacrylate
RL: TEM (Technical or engineered material use); USES (Uses)
(Sartomer CD 572; electrophotog. photoconductor and process for its manufacturing)
IT 50586-59-9, Curene 93
RL: TEM (Technical or engineered material use); USES (Uses)
(Voranol 234-630; electrophotog. photoconductor and process for its manufacturing)
IT 84593-42-0, Mondur CD 136457-10-8, Tinuvin 213
204019-31-8, Acclaim 6320 752252-67-8, SarCure SR 1129
752252-69-0, SarCure SR 1137
RL: TEM (Technical or engineered material use); USES (Uses)
(electrophotog. photoconductor and process for its manufacturing)
REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L31 ANSWER 5 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2004:996243 HCAPLUS Full-text
DOCUMENT NUMBER: 141:424846
TITLE: Benzotriazole unit-containing polymers for use in optical devices
INVENTOR(S): Rogers, Jonathan; Craig, Michael Robert; Schaefer, Thomas
PATENT ASSIGNEE(S): Ciba Specialty Chemicals Holding Inc., Switz.
SOURCE: PCT Int. Appl., 67 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2004099285	A2	20041118	WO 2004-EP50606	2004 0426
			<--	
WO 2004099285	A3	20051124		
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
EP 1620486	A2	20060201	EP 2004-741481	2004 0426
			<--	
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR				
CN 1784445	A	20060607	CN 2004-80012058	2004 0426

				<--	
JP 2006526671	T	20061124	JP 2006-505574	2004 0426	
				<--	
US 20070043204	A1	20070222	US 2005-553775	2005 1020	
				<--	
PRIORITY APPLN. INFO.:			EP 2003-405317	2003 0505	A
				<--	
			WO 2004-EP50606	2004 0426	W
				<--	

ED Entered STN: 19 Nov 2004

AB The present invention relates to polymers comprising benzotriazole-containing repeating units. Optical devices such as electroluminescent or photovoltaic devices, made from the polymers of the present invention, can show significant advantages in color purity, device efficiency and/or operational lifetime. In addition, the polymers can have good solubility characteristics and relatively high glass transition temps., which facilitates their fabrication into coatings and films that are relatively thin, thermally stable, and relatively free of defects. Thus, stirring a solution of bis(1,5-cyclooctadiene)nickel 2.0 and 2,2'-bipyridyl 1.14 in PhMe (7.0 mL) at 80° for 1 h under Ar and darkness, adding 3-bromo-2-(3'-bromo-4'-methoxyphenyl)benzotriazole 0.23 and 2,7-dibromo-9,9-dihexylfluorene 1.50 g dissolved in PhMe (7 mL), purging with Ar, heating with a solution of a Ni complex at 80° for 17 h and working up gave a copolymer having benzotriazole repeating unit with Mw 650,000 and polydispersity 2.21.

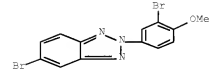
IT 794518-77-7P 794518-81-3P 794518-84-6P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(manufacture of benzotriazole unit-containing polymers for use in optical devices)

RN 794518-77-7 HCAPLUS

CN 2H-Benzotriazole, 5-bromo-2-(3-bromo-4-methoxyphenyl)-, polymer with 2,7-dibromo-9,9-dihexyl-9H-fluorene (9CI) (CA INDEX NAME)

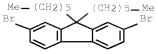
CM 1

CRN 794518-76-6
CMF C13 H9 Br2 N3 O



CM 2

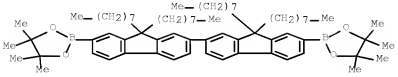
CRN 189367-54-2
CMF C25 H32 Br2



RN 794518-81-3 HCAPLUS
CN 2H-Benzotriazole, 5-bromo-2-(6-bromo-2-methoxy-1-naphthalenyl)-, polymer with 2,2'-(9,9,9',9'-tetraoctyl[2,2'-bi-9H-fluorene]-7,7'-diyl)bis[4,4,5,5-tetramethyl-1,3,2-dioxaborolane] (9CI) (CA INDEX NAME)

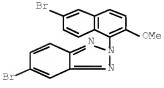
CM 1

CRN 794518-80-2
CMF C70 H104 B2 O4



CM 2

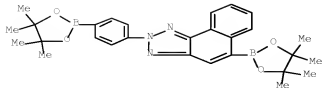
CRN 794518-79-9
CMF C17 H11 Br2 N3 O



RN 794518-84-6 HCAPLUS
CN 2H-Naphtho[1,2-d]triazole, 5-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-2-[4-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)phenyl]-, polymer with 1,4-dibromo-2,5-bis(octyloxy)benzene (9CI) (CA INDEX NAME)

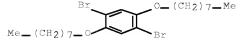
CM 1

CRN 794518-83-5
CMF C28 H33 B2 N3 O4



CM 2

CRN 156028-40-9
CMF C22 H36 Br2 O2



IC ICM C08G061-12
CC 37-3 (Plastics Manufacture and Processing)
Section cross-reference(s): 73, 74
ST optical device color purity soly benzotriazole polymer; coatability benzotriazole polymer coating film optical device; glass transition temp benzotriazole polymer optical device
IT Electroluminescent devices
Photoelectric devices
(manufacture of benzotriazole unit-containing polymers for use in optical devices)
IT 95-14-7DP, 1H-Benzotriazole, polymers 794518-77-7P 794518-81-3P 794518-84-6P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(manufacture of benzotriazole unit-containing polymers for use in optical devices)
REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L31 ANSWER 6 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2004:616437 HCAPLUS Full-text
DOCUMENT NUMBER: 141:412461
TITLE: Migration of reactable UVAs and HALS in automotive plastic coatings
AUTHOR(S): Yaneff, Philip V.; Adamsons, Karlis; Cliff, Nancy; Kanouni, Mouhcine
CORPORATE SOURCE: DuPont Performance Coatings, Ajax, ON, L1S 1R6, Can.
SOURCE: JCT Research (2004), 1(3), 201-212
CODEN: JRCEB5; ISSN: 1547-0091
PUBLISHER: Federation of Societies for Coatings Technology
DOCUMENT TYPE: Journal
LANGUAGE: English
ED Entered STN: 02 Aug 2004
AB Loss of light stabilizers from automotive finishes can significantly reduce the durability of coatings on plastic substrates. Minimizing movement by retaining the stabilizers in the targeted layer can greatly improve coating longevity. This article

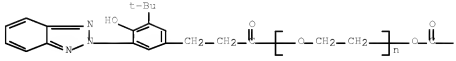
examines the migratory patterns of a series of traditional UVA and HALS additives in fully formulated 1K silane crosslinked coatings applied over both plastic and steel substrates, comparing their migratory patterns to that of reactable light stabilizers containing hydroxyl functionality. Anal. of the coating layers with the various UVAs and HALS revealed that functionalization of the light stabilizer with reactable hydroxy groups can prevent migration into the plastic; whereas nonreactable light stabilizers migrate into lower coating system layers and even into the plastic substrate. The greatest extent of migration does not occur during initial cure of the wet coating, but during exposure. Significant depletion of the nonreactable light stabilizers from the topcoat occurs as early as 1500 h of Xenon boro/boro exposure.

IT 104810-47-1 104810-48-2
RL: MOA (Modifier or additive use); PRP (Properties); USES (Uses)
(stabilizer; migration of reactive UV and hindered amine light stabilizers in automotive plastic coatings)

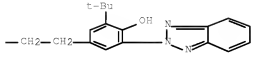
RN 104810-47-1 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-ω-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropoxy]- (CA INDEX NAME)

PAGE 1-A

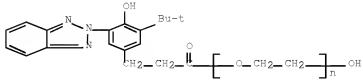


PAGE 1-B



RN 104810-48-2 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-ω-hydroxy- (CA INDEX NAME)



CC 42-5 (Coatings, Inks, and Related Products)

IT Automobiles
Coating materials
Diffusion
ESR (electron spin resonance)
Light stabilizers
Oxidation, photochemical
UV absorption

UV stabilizers
(migration of reactive UV and hindered amine light stabilizers in automotive plastic coatings)
IT 73936-91-1 104810-47-1 104810-48-2
122586-52-1 137759-38-7 150686-79-6 178905-31-2
RL: MOA (Modifier or additive use); PRP (Properties); USES (Uses)
(stabilizer; migration of reactive UV and hindered amine light stabilizers in automotive plastic coatings)
REFERENCE COUNT: 12 THERE ARE 12 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

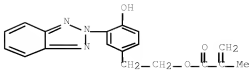
L31 ANSWER 7 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2003:947956 HCAPLUS Full-text
DOCUMENT NUMBER: 140:11343
TITLE: Polymer electrolytes easily undergoing photocrosslinking and electrochromic devices therewith
INVENTOR(S): Nishikitani, Yoshinori; Asano, Takeshi; Ikai, Keizo
PATENT ASSIGNEE(S): Nippon Oil Corporation, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003346553	A	20031205	JP 2002-150533	2002 0524 <--
JP 4166505	B2	20081015		
PRIORITY APPLN. INFO.:			JP 2002-150533	2002 0524 <--

ED Entered STN: 05 Dec 2003
AB The electrolytes, showing high ion conductivity and good dimensional accuracy, comprise photocured products of liquid mixts. containing polymers from R1R2C:CR3(CO2R4)nR5 [R1-R3 = H, C1-5 alkyl; R4 = C1-10 alkylene, C6-12 arylene, (CH2CHRO)r (R = H, C1-5 alkyl; r = 1-20); R5 = H, C1-10 alkyl, C6-12 aryl, C1-10 alkoxyl; n = 0, 2], R'1R'3C:CR'2CO2CH2CH:CH2 (R'1-R'3 = H, C1-5 alkyl), and optional (UV-absorbing) comonomers, solvents, support electrolytes, and photopolymn. initiators.
IT 628684-62-8DP, Allyl methacrylate-methyl methacrylate-Ruva 93 copolymer, tetrabutylammonium complexes, tetrafluoroborate-containing
RL: DEV (Device component use); IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinked; photocrosslinkable polymer electrolytes showing min. curing shrinkage for electrochromic devices)
RN 628684-62-8 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with methyl 2-methyl-2-propenoate and 2-propenyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

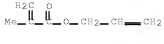
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 96-05-9
CMF C7 H10 O2



CM 3

CRN 80-62-6
CMF C5 H8 O2

IC ICM H01B001-06
ICS C08F002-44; C08F220-10; C08F220-40; C08F299-00
CC 76-2 (Electric Phenomena)
Section cross-reference(s): 38
IT Electrochromic devices
Polymer electrolytes
(photocrosslinkable polymer electrolytes showing min. curing shrinkage for electrochromic devices)
IT 7439-93-2DP, Lithium, methacrylate polymer complexes, perchlorate-containing 26715-19-5DP, Allyl methacrylate-methyl methacrylate copolymer, tetrabutylammonium complexes, tetrafluoroborate-containing 628684-62-8DP, Allyl methacrylate-methyl methacrylate-Ruva 93 copolymer, tetrabutylammonium complexes, tetrafluoroborate-containing
RL: DEV (Device component use); IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinked; photocrosslinkable polymer electrolytes showing min. curing shrinkage for electrochromic devices)

L31 ANSWER 8 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2003:586727 HCAPLUS Full-text
DOCUMENT NUMBER: 139:136074
TITLE: Pigment sensitized photoelectrochemical cell
INVENTOR(S): Noda, Nobuhisa; Nakamura, Junichi
PATENT ASSIGNEE(S): Nippon Shokubai Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent

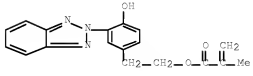
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003217690	A	20030731	JP 2002-10691	2002 0118
			<--	
PRIORITY APPLN. INFO.:			JP 2002-10691	2002 0118
			<--	

ED Entered STN: 31 Jul 2003
AB The photoelectrochem. cell has a UV shielding layer on its light incident side, where the layer is a formed from a composition containing a copolymer of a monomer having UV absorbing groups, a monomer having C≥4 alkyl groups, and/or a monomer having UV stabilizing groups; or a composition containing a polymer of a monomer having C≥4 alkyl groups and/or a monomer having UV stabilizing groups mixed with a UV absorbing additive.
IT 287736-69-0 569367-49-3 569367-51-7
569367-53-9 569367-55-1
RL: DEV (Device component use); USES (Uses)
(Uv shielding coatings for pigment sensitized photoelectrochem. cells)
RN 287736-69-0 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate (CA INDEX NAME)

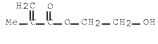
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 868-77-9
CMF C6 H10 O3



CM 3

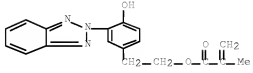
CRN 80-62-6

CMF C5 H8 O2

RN 569367-49-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with cyclohexyl 2-methyl-2-propenoate, 2-ethylhexyl 2-propenoate,
2-hydroxyethyl 2-methyl-2-propenoate and methyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

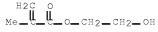
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



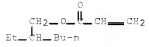
CM 2

CRN 868-77-9
CMF C6 H10 O3



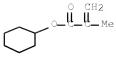
CM 3

CRN 103-11-7
CMF C11 H20 O2



CM 4

CRN 101-43-9
CMF C10 H16 O2



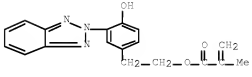
CM 5

CRN 80-62-6
CMF C5 H8 O2

RN 569367-51-7 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with cyclohexyl 2-methyl-2-propenoate, 2-ethylhexyl 2-propenoate,
2-hydroxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate
and 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate
(9CI) (CA INDEX NAME)

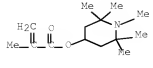
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



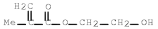
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



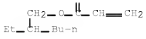
CM 3

CRN 868-77-9
CMF C6 H10 O3



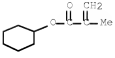
CM 4

CRN 103-11-7
CMF C11 H20 O2



CM 5

CRN 101-43-9
CMF C10 H16 O2



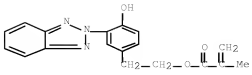
CM 6

CRN 80-62-6
CMF C5 H8 O2

RN 569367-53-9 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with cyclohexyl 2-methyl-2-propenoate, 2-ethylhexyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

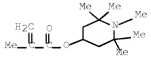
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



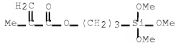
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



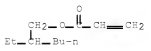
CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si



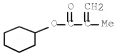
CM 4

CRN 103-11-7
CMF C11 H20 O2



CM 5

CRN 101-43-9
CMF C10 H16 O2



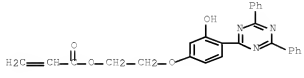
CM 6

CRN 80-62-6
CMF C5 H8 O2

RN 569367-55-1 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with cyclohexyl 2-methyl-2-propenoate,
2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]ethyl
2-propenoate, 2-ethylhexyl 2-propenoate, 2-hydroxyethyl
2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and
1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

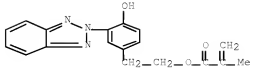
CM 1

CRN 176225-24-4
CMF C26 H21 N3 O4



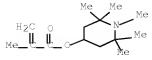
CM 2

CRN 96478-09-0
CMF C18 H17 N3 O3



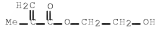
CM 3

CRN 68548-08-3
CMF C14 H25 N O2



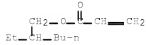
CM 4

CRN 868-77-9
CMF C6 H10 O3



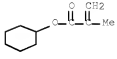
CM 5

CRN 103-11-7
CMF C11 H20 O2



CM 6

CRN 101-43-9
CMF C10 H16 O2



CM 7

CRN 80-62-6
CMF C5 H8 O2

IC ICM H01M014-00
ICS H01L031-04

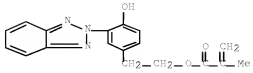
```
CC   52-2 (Electrochemical, Radiational, and Thermal Energy Technology)
ST   pigment sensitized photoelectrochem cell UV shielding
     polymer layer
IT   Photoelectrochemical cells
     UV shields
        (Uv shielding coatings for pigment sensitized
        photoelectrochem. cells)
IT   26355-01-1   28549-51-1 287736-69-0   569367-47-1
     569367-49-3 569367-51-7 569367-53-9
     569367-55-1   569367-57-3
     RL: DEV (Device component use); USES (Uses)
        (Uv shielding coatings for pigment sensitized
        photoelectrochem. cells)

L31  ANSWER 9 OF 29  HCAPLUS  COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER:         2003:520420  HCAPLUS  Full-text
DOCUMENT NUMBER:          139:86337
TITLE:                    Antisoiling, weather-resistant waterproof
                          sheets
INVENTOR(S):              Suzuki, Kenji
PATENT ASSIGNEE(S):       Hiraoka and Co., Ltd., Japan
SOURCE:                   Jpn. Kokai Tokkyo Koho, 28 pp.
                          CODEN: JKXXAF
DOCUMENT TYPE:            Patent
LANGUAGE:                 Japanese
FAMILY ACC. NUM. COUNT:   1
PATENT INFORMATION:

     PATENT NO.          KIND   DATE        APPLICATION NO.        DATE
     ----------------    ----   --------    --------------------
     --------
     JP 2003191386        A     20030708    JP 2002-93052
                                                                   2002
                                                                   0328
                                                  <--
PRIORITY APPLN. INFO.:                       JP 2001-95879      A
                                                                   2001
                                                                   0329
                                                  <--
                                             JP 2001-318365     A
                                                                   2001
                                                                   1016
                                                  <--
ED   Entered STN:  09 Jul 2003
AB   The sheets, useful for medium to large-scale tents, etc., consist of a base sheet
     comprising a base fabric and polymer layer(s) containing natural rubber, synthetic
     rubber, and/or synthetic resins formed on at least one side of the base fabric, and
     hydrophilic coating layer(s) containing organosilicates and/or their condensates formed
     on the polymer layer(s).  Thus, a polyester fabric was coated with a composition
     containing self-emulsifiable acrylic resin (Nipol SX 1706) 70, primary amino group-
     containing acrylic resin (Polyment NK-CK 200) 30, light stabilizer (Tinofast RSC) 0.2,
     UV absorber (Tinuvin 213) 0.2, TiO2 3, and 5-chlorobenzotriazole 0.1 part on the both
     sides and dried to give a base sheet, which was coated with an aqueous MeOH solution of
     Me silicate partial hydrolytic condensation product (MKC Silicate MS 56) 100, γ-
     glycidoxypropyltrimethoxysilane 10, and organometallic chelating agent 0.3 part on the
     both sides and dried to give a product showing long-lasting antisoiling properties
     during outdoor exposure.
IT   153175-43-0, Puva 30M
     RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical
     or engineered material use); USES (Uses)
        (additive migration-proofing layer; antisoiling,
        weather-resistant waterproof sheets coated with silicates)
RN   153175-43-0  HCAPLUS
CN   2-Propenoic acid, 2-methyl-,
     2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
     with methyl 2-methyl-2-propenoate  (CA INDEX NAME)
```

CM 1

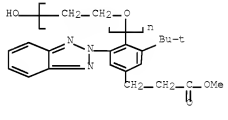
CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 80-62-6
CMF C5 H8 O2

IT 136457-10-8, Tinuvin 213
RL: MOA (Modifier or additive use); USES (Uses)
(base fabric coating containing; antisoiling, weather-resistant waterproof sheets coated with silicates)
RN 136457-10-8 HCAPLUS
CN Poly(oxy-1,2-ethanediyl), α-[2-(2H-benzotriazol-2-yl)-6-(1,1-dimethylethyl)-4-(3-methoxy-3-oxopropyl)phenyl]-ω-hydroxy- (CA INDEX NAME)



IC ICM B32B027-00
ICS C09K003-00
CC 38-3 (Plastics Fabrication and Uses)
Section cross-reference(s): 40
IT 9002-89-5, PVA 117 9002-98-6D, Polyethylenimine, graft polymers with acrylic resins 9011-14-7, Methyl methacrylate resin 25068-38-6, Epikote 828 25684-76-8, Kynar 7201 64735-01-9, Elastron E 37 153175-43-0, Puva 30M 159131-89-2, Polyment NK 380 364053-83-8, Sony Bond SC 474
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(additive migration-proofing layer; antisoiling, weather-resistant waterproof sheets coated with silicates)

IT 91-76-9, Benzoguanamine 3319-31-1, Tris-2-ethylhexyl trimellitate 27178-16-1, Diisodecyl adipate 28553-12-0, Diisononyl phthalate 57583-54-7, Fyrolflex RDP 136457-10-8, Tinuvin 213 204143-67-9, Tinofast RSC 461642-21-7, NK Assist OX 473900-22-0, Epostar GP 50
RL: MOA (Modifier or additive use); USES (Uses)
(base fabric coating containing; antisoiling, weather-resistant waterproof sheets coated with silicates)

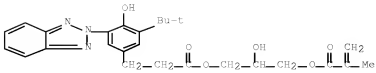
L31 ANSWER 10 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2003:271851 HCAPLUS Full-text
DOCUMENT NUMBER: 138:289107
TITLE: Fluororesin powder coating compositions with weather resistance
INVENTOR(S): Kasahara, Kiyoshi; Yamauchi, Suguru; Unoki, Masao
PATENT ASSIGNEE(S): Asahi Glass Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003105250	A	20030409	JP 2001-298287	2001 0927 <--
PRIORITY APPLN. INFO.:			JP 2001-298287	2001 0927 <--

ED Entered STN: 09 Apr 2003
AB Title compns. contain fluororesins and benzotriazole vinyl compound-based UV-absorbing resins. A powdered composition containing Bu methacrylate-2-hydroxyethyl methacrylate-Me methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy-2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole copolymer, cyclohexyl vinyl ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether copolymer, and ct B 1530 was electrodeposited on a white urethane base composition-coated plate and cured at 180° for 20 min to form a film showing 60° gloss 100 with 99% retention after 2,000 h under weatherometer and good adhesion to white base coat.
IT 505023-79-0P, Cyclohexyl vinyl ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether-butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole-Vestagon B 1530 copolymer
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(cured; powdered fluororesin coatings containing benzotrizole-containing acrylic resins for weather resistance)
RN 505023-79-0 HCAPLUS
CN Benzenepropanoic acid, 3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, 2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl ester, polymer with butyl 2-methyl-2-propenoate, chlorotrifluoroethene, 4-(ethenyloxy)-1-butanol, (ethenyloxy)cyclohexane, 2-hydroxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and Vestagon B 1530 (9CI) (CA INDEX NAME)

CM 1

CRN 135590-53-3
CMF C26 H31 N3 O6



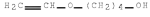
CM 2

CRN 81647-82-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

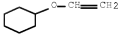
CM 3

CRN 17832-28-9
CMF C6 H12 O2



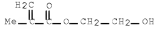
CM 4

CRN 2182-55-0
CMF C8 H14 O



CM 5

CRN 868-77-9
CMF C6 H10 O3



CM 6

CRN 97-88-1
CMF C8 H14 O2

CM 7

CRN 80-62-6
CMF C5 H8 O2

CM 8

CRN 79-38-9
CMF C2 Cl F3

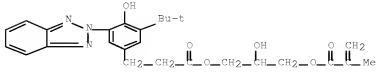
IT 505023-82-5P, Butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(powdered fluororesin coatings containing benzotrizole-containing acrylic resins for weather resistance)

RN 505023-82-5 HCAPLUS

CN Benzenepropanoic acid, 3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, 2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl ester, polymer with butyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

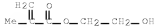
CM 1

CRN 135590-53-3
CMF C26 H31 N3 O6



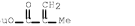
CM 2

CRN 868-77-9
CMF C6 H10 O3



CM 3

CRN 97-88-1
CMF C8 H14 O2



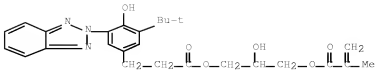
CM 4

CRN 80-62-6
CMF C5 H8 O2

IT 505023-80-3P, Cyclohexyl vinyl ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether-isobutyl vinyl ether-butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole-Vestagon B 1530 copolymer
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(powdered fluororesin coatings containing benzotrizole-containing acrylic resins for weather resistance)
RN 505023-80-3 HCAPLUS
CN Benzenepropanoic acid, 3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, 2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl ester, polymer with butyl 2-methyl-2-propenoate, chlorotrifluoroethene, 4-(ethenyloxy)-1-butanol, (ethenyloxy)cyclohexane, 1-(ethenyloxy)-2-methylpropane, 2-hydroxyethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate and Vestagon B 1530 (9CI) (CA INDEX NAME)

CM 1

CRN 135590-53-3
CMF C26 H31 N3 O6



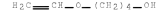
CM 2

CRN 81647-82-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

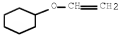
CM 3

CRN 17832-28-9
CMF C6 H12 O2



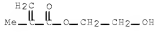
CM 4

CRN 2182-55-0
CMF C8 H14 O



CM 5

CRN 868-77-9
CMF C6 H10 O3



CM 6

CRN 109-53-5
CMF C6 H12 O

CM 7

CRN 97-88-1
CMF C8 H14 O2

CM 8

CRN 80-62-6
CMF C5 H8 O2

CM 9

CRN 79-38-9
CMF C2 Cl F3

IC ICM C09D127-12
ICS C09D005-03; C09D133-14; C09D133-24; C09D157-12
CC 42-10 (Coatings, Inks, and Related Products)
IT 505023-79-0P, Cyclohexyl vinyl
ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether-butyl
methacrylate-2-hydroxyethyl methacrylate-methyl
methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-
2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole-Vestagon B
1530 copolymer
RL: IMF (Industrial manufacture); TEM (Technical or engineered
material use); PREP (Preparation); USES (Uses)
(cured; powdered fluororesin coatings containing benzotrizole-containing
acrylic resins for Weather resistance)
IT 29697-44-7P, Ethylene-propene-tetrafluoroethylene copolymer
505023-81-4P, Butyl methacrylate-tert-butyl
methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate
copolymer 505023-82-5P, Butyl
methacrylate-2-hydroxyethyl methacrylate-methyl
methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-
2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation);
TEM (Technical or engineered material use); PREP (Preparation);
USES (Uses)
(powdered fluororesin coatings containing benzotrizole-containing acrylic

resins for weather resistance)
IT 90S023-80-3P, Cyclohexyl vinyl ether-chlorotrifluoroethylene-4-hydroxybutyl vinyl ether-isobutyl vinyl ether-butyl methacrylate-2-hydroxyethyl methacrylate-methyl methacrylate-2-[2'-hydroxy-3'-tert-butyl-5'-2-(3-methacryloyloxy)-2-hydroxypropoxycarbonyl)ethylphenyl]-2H-benzotriazole-Vestagon B 1530 copolymer
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(powdered fluororesin coatings containing benzotrizole-containing acrylic resins for weather resistance)

L31 ANSWER 11 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2003:118356 HCAPLUS Full-text
DOCUMENT NUMBER: 138:178010
TITLE: Ultraviolet stabilizing materials having a solubilizing moiety for use in electrochromic devices
INVENTOR(S): Giri, Punam; Kloeppner, Leroy J.; Baumann, Kelvin L.; Lomprey, Jeffrey R.; Guarr, Thomas F.
PATENT ASSIGNEE(S): USA
SOURCE: U.S. Pat. Appl. Publ., 13 pp., Cont.-in-part of U. S. 6,445,486.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 5
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 20030030883	A1	20030213	US 2002-211485	20020802
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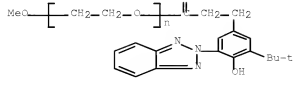
US 6614578	B2	20030902		
US 6262832	B1	20010717	US 1999-454043	19991203
			<--	
US 6445486	B1	20020903	US 2000-724118	20001128
			<--	
WO 2004013688	A1	20040212	WO 2003-US23608	20030729
			<--	
W: AT, AU, BG, BR, CA, CH, CN, CZ, DE, DK, ES, FI, GB, GE, HU, ID, IL, IN, JP, KR, MX, NO, NZ, PL, PT, RO, RU, SE, SG, SK, TR, UA, YU, ZA				
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR				
AU 2003261284	A1	20040223	AU 2003-261284	20030729
			<--	
EP 1540413	A1	20050615	EP 2003-766942	20030729
			<--	
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
PRIORITY APPLN. INFO.:			US 1999-454043	A2

1999
1203
<--
US 2000-724118 A2
2000
1128
<--
US 2002-211485 A
2002
0802
<--
WO 2003-US23608 W
2003
0729
<--

OTHER SOURCE(S): MARPAT 138:178010
ED Entered STN: 14 Feb 2003
AB An electrochromic medium for use in electrochromic devices is described which comprises ≥1 solvent; an anodic material; a cathodic material, where both of the anodic and cathodic materials are electroactive and ≥1 of the anodic and cathodic materials is electrochromic; and an UV stabilizing material, where the UV stabilizing material includes a solubilizing moiety which serves to increase solubility of the UV stabilizing material relative to the same without the solubilizing moiety. Electrochromic devices are discussed which comprise a first substantially transparent substrate having an elec. conductive material; a second substrate having an elec. conductive material; and an electrochromic medium contained within a chamber positioned between the first and second substrates which comprises ≥1 solvent; an anodic material; a cathodic material, where both of the anodic and cathodic materials are electroactive and ≥1 of the anodic and cathodic materials is electrochromic; and an UV stabilizing material, where the UV stabilizing material includes a solubilizing moiety which serves to increase solubility of the UV stabilizing material relative to the same without the solubilizing moiety. Electrochromic media and devices in which the UV stabilizing material is a Ph benzotriazole derivative including a solubilizing moiety are also discussed.
IT 497068-80-1P
RL: DEV (Device component use); PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(UV stabilizing materials having solubilizing moiety for use in electrochromic devices)
RN 497068-80-1 HCAPLUS
CN Poly(oxy-1,2-ethanediyl), α-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-ω-methoxy- (9CI) (CA INDEX NAME)



IC ICM G02F001-15
INCL 359265000
CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
Section cross-reference(s): 22, 68, 74, 76
IT Coating materials
(reflective, substrate of electrochromic device plated with; UV stabilizing materials having solubilizing moiety for use in electrochromic devices)

IT 84267-86-7P 497068-76-5P 497068-79-8P 497068-80-1P
RL: DEV (Device component use); PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(UV stabilizing materials having solubilizing moiety for use in electrochromic devices)
IT 7440-16-6, Rhodium, uses 7440-16-6D, Rhodium, alloy 7440-18-8, Ruthenium, uses 7440-18-8D, Ruthenium, alloy 7440-22-4, Silver, uses 7440-22-4D, Silver, alloy 7440-47-3, Chromium, uses 7440-47-3D, Chromium, alloy
RL: TEM (Technical or engineered material use); USES (Uses)
(substrate of electrochromic device plated with reflective; UV stabilizing materials having solubilizing moiety for use in electrochromic devices)

L31 ANSWER 12 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2003:111338 HCAPLUS Full-text
DOCUMENT NUMBER: 138:178317
TITLE: Optical film containing benzophenone and/or benzotriazole UV absorber for excellent color reproducibility, polarizing plate and optical imaging display
INVENTOR(S): Michihata, Isamu; Shimizu, Kunio; Saito, Koichi
PATENT ASSIGNEE(S): Konica Co., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

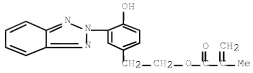
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003043259	A	20030213	JP 2001-233464	2001 0801
			<--	
JP 2008304930	A	20081218	JP 2008-184714	2008 0716
			<--	
PRIORITY APPLN. INFO.:			JP 2001-233464 A3	2001 0801
			<--	

ED Entered STN: 13 Feb 2003
AB The optical film contains a benzophenone and/or benzotriazole UV absorber, and has a spectral transmittance 50-95% at 390 nm and a spectral transmittance ≤5% at 350 nm. The optical film is based on a cellulose ester, and has a film thickness 20-65 μm. The polarizing plate and the optical imaging device such as LCD and EL devices are also claimed.
IT 153175-43-0, PUVA-30M
RL: DEV (Device component use); USES (Uses)
(optical film containing benzophenone and/or benzotriazole UV absorber for polarizing plate and optical imaging display)
RN 153175-43-0 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0

CMF C18 H17 N3 O3



CM 2

CRN 80-62-6
CMF C5 H8 O2

IC ICM G02B005-30
ICS C08J005-18; C08K003-36; C08K005-07; C08K005-3475; C08L001-10; C08L101-00; G02B005-22; G02F001-1335; G09F009-00
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 25, 28, 41, 73
ST optical film benzophenone benzotriazole UV absorber; liq crystal display electroluminescence device
IT Electroluminescent devices
Liquid crystal displays
(optical film containing benzophenone and/or benzotriazole UV absorber for)
IT Optical films
Polarizers
UV stabilizers
(optical film containing benzophenone and/or benzotriazole UV absorber for polarizing plate and optical imaging display)
IT 9004-34-6, Cellulose, uses
RL: DEV (Device component use); USES (Uses)
(ester, support; optical film containing benzophenone and/or benzotriazole UV absorber for polarizing plate and optical imaging display)
IT 131-57-7 23328-53-2 38080-43-2 153175-43-0, PUVA-30M
RL: DEV (Device component use); USES (Uses)
(optical film containing benzophenone and/or benzotriazole UV absorber for polarizing plate and optical imaging display)

L31 ANSWER 13 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2002:848332 HCAPLUS Full-text
DOCUMENT NUMBER: 137:343669
TITLE: Organic electroluminescent devices
INVENTOR(S): Kato, Hiroshi
PATENT ASSIGNEE(S): Ricoh Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002324664	A	20021108	JP 2001-131017	2001 0427
			<--	
PRIORITY APPLN. INFO.:			JP 2001-131017	2001 0427
			<--	

ED Entered STN: 08 Nov 2002

AB The devices comprise: a glass substrate; a polymer layer containing a pendant-type UV absorber; an ITO 1st electrode; a hole transport, a phosphor, an electron transport and a metal 2nd electrode.

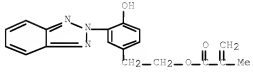
IT 153175-43-0, PUVA-30M
RL: DEV (Device component use); USES (Uses)
(organic electroluminescent devices)

RN 153175-43-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 80-62-6
CMF C5 H8 O2

IC ICM H05B033-04
ICS H05B033-14; H05B033-22

CC 73-5 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)

IT Anodes
Cathodes
Electrodes
Electron transport
Hole transport
Phosphors
Seals (parts)
UV stabilizers
(organic electroluminescent devices)

IT 50926-11-9, ITO 76185-65-4 80223-29-6 134917-82-1

153175-43-0, PUVA-30M 157357-76-1
RL: DEV (Device component use); USES (Uses)
(organic electroluminescent devices)

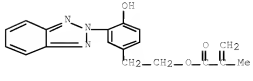
L31 ANSWER 14 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2002:606627 HCAPLUS Full-text
DOCUMENT NUMBER: 137:161224
TITLE: Low reflectance laminate and its production
INVENTOR(S): Murakami, Takashi; Takiyama, Nobuyuki; Fukuda, Kazuhiro
PATENT ASSIGNEE(S): Konica Co., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002228803	A	20020814	JP 2001-21573	2001 0130
			<--	
PRIORITY APPLN. INFO.:			JP 2001-21573	2001 0130
			<--	

ED Entered STN: 14 Aug 2002
AB The invention refers to a low reflection laminate, suitable for use in cathode ray tubes, plasma display panels, solar cells, liquid crystal displays, etc., wherein a substrate is placed between two electrodes, one of which is a roll electrode with surface roughness Rmax < 10 μm and the other is coated with an inorg. material, and the substrate is coated with a fluorine, silicon or titanium thin film using plasma discharge treatment in order to produce a laminate with minimal reflectivity and minimal contamination from the plasma discharge process.
IT 153175-43-0, PUVA-30M
RL: DEV (Device component use); USES (Uses)
(low reflectance laminate and production)
RN 153175-43-0 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 80-62-6
CMF C5 H8 O2

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IC   ICM  G02B001-11
     ICS  B32B027-00; B32B027-30; C08J007-00; C23C016-40; G02B001-10;
          C08L001-00
CC   73-11 (Optical, Electron, and Mass Spectroscopy and Other Related
     Properties)
ST   low reflectance laminate plasma discharge treatment
     antireflection film
IT   Antireflective films
     Laminated materials
     Optical reflection
     Plasma
        (low reflectance laminate and production)
IT   84-72-0, Ethyl phthalyl ethyl glycolate   115-86-6, Triphenyl
     phosphate   3896-11-5, Tinuvin 326   7440-21-3, Silicon, uses
     7440-32-6, Titanium, uses   7631-86-9, Silica, uses   7782-41-4,
     Fluorine, uses   9012-09-3, Triacetyl cellulose   23328-53-2,
     Tinuvin 171   67653-78-5, Dipentaerythritol hexaacrylate
     homopolymer   83044-89-7, Tinuvin 109 153175-43-0,
     PUVA-30M   200734-67-4, KE-604
     RL: DEV (Device component use); USES (Uses)
        (low reflectance laminate and production)

L31  ANSWER 15 OF 29  HCAPLUS  COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER:         2002:107451  HCAPLUS  Full-text
DOCUMENT NUMBER:          136:169112
TITLE:                    Colored resin emulsion, ink for ink-jet
                          printing, electrocoating fluid and color
                          filter
INVENTOR(S):              Ishii, Masahiro; Shichiri, Tokushige; Oguchi,
                          Yoshiyuki; Toyoshima, Katsunori; Ueda,
                          Michihisa
PATENT ASSIGNEE(S):       Sekisui Chemical Co. Ltd., Japan
SOURCE:                   PCT Int. Appl., 140 pp.
                          CODEN: PIXXD2
DOCUMENT TYPE:            Patent
LANGUAGE:                 Japanese
FAMILY ACC. NUM. COUNT:   2
PATENT INFORMATION:

     PATENT NO.          KIND   DATE        APPLICATION NO.        DATE
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     WO 2002010280        A1    20020207    WO 2001-JP6518
                                                                   2001
                                                                   0730
                                                  <--
         W:  CA, CN, KR, SG, US
         RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU,
             MC, NL, PT, SE, TR
     JP 2002105272        A     20020410    JP 2000-312154
                                                                   2000
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     JP 2002356602        A     20021213    JP 2001-229429
                                                                   2001
                                                                   0730
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PRIORITY APPLN. INFO.:                     JP 2000-229324      A
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	JP 2000-242820	A	2000 0810
	<--		
	JP 2000-267377	A	2000 0904
	<--		
	JP 2000-340679	A	2000 1108
	<--		
	JP 2001-789	A	2001 0105
	<--		
	JP 2001-28322	A	2001 0205
	<--		
	JP 2001-99913	A	2001 0330
	<--		

ED Entered STN: 10 Feb 2002

AB The present invention relates to a colored resin emulsion which comprises an aqueous medium and, dispersed in the medium, colorant-incorporating resin particles comprising a colorant and a vinyl resin which is prepared by polymerizing a mixed monomer comprising 100 parts by weight of a hydrophobic vinyl monomer, 1 to 30 parts by weight of a vinyl monomer having an anionic or cationic group and 1 to 55 parts by weight of a vinyl monomer having a nonionic group; and an ink for ink-jet printing, an electrocoating fluid and a color filter using the colored resin emulsion. The colored resin emulsion exhibits excellent stability, weatherability and resistance to light. Thus, N-butoxymethylacrylamide 100, hydroxyethyl methacrylate 11.8, methacrylic acid 5.9 parts were polymerized in 341.0 parts Et acetate containing 11.8 parts V 65, 23.5 parts Orasol Red G was added to give a colored vinyl type resin solution, which was stirred with NH3 aqueous solution to give a colored resin emulsion with average particle size 76 nm. A ink-jet printing ink comprised the resulting emulsion (20%-solids) 50, glycerin 20, and water 30 parts.

IT 395681-56-8P 395681-58-0P

RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(colored resin emulsions for ink-jet printing inks, electrocoating fluids and color filters)

RN 395681-56-8 HCAPLUS

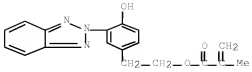
CN 2-Propenoic acid, 2-methyl-, polymer with 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate, N-(butoxymethyl)-2-propenamide, 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate, ammonium salt (9CI) (CA INDEX NAME)

CM 1

CRN 395681-55-7
CMF (C18 H17 N3 O3 . C8 H15 N O2 . C6 H10 O3 . C5 H8 O2 . C4 H6 O2)x
CCI PMS

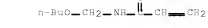
CM 2

CRN 96478-09-0
CMF C18 H17 N3 O3



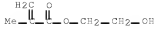
CM 3

CRN 1852-16-0
CMF C8 H15 N O2



CM 4

CRN 868-77-9
CMF C6 H10 O3



CM 5

CRN 80-62-6
CMF C5 H8 O2

CM 6

CRN 79-41-4
CMF C4 H6 O2

RN 395681-58-0 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, polymer with
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl

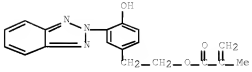
2-methyl-2-propenoate, N-butoxy-2-propenamide, 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate, ammonium salt (9CI) (CA INDEX NAME)

CM 1

CRN 395681-57-9
CMF (C18 H17 N3 O3 . C7 H13 N O2 . C6 H10 O3 . C5 H8 O2 . C4 H6 O2)x
CCI PMS

CM 2

CRN 96478-09-0
CMF C18 H17 N3 O3

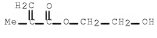


CM 3

CRN 4203-85-4
CMF C7 H13 N O2

CM 4

CRN 868-77-9
CMF C6 H10 O3



CM 5

CRN 80-62-6
CMF C5 H8 O2

CM 6

CRN 79-41-4
CMF C4 H6 O2

IC ICM C08L057-00
ICS C08J003-03; C09D011-00; C08J003-24; B41M005-00; G02B005-20;
G02B005-22
CC 42-12 (Coatings, Inks, and Related Products)
Section cross-reference(s): 37, 38, 73
IT Coloring materials
Electrodeposits
Optical filters
Pigments, nonbiological
(colored resin emulsions for ink-jet printing inks,
electrocoating fluids and color filters)
IT 208838-83-9P 395681-50-2P 395681-52-4P 395681-54-6P
395681-56-8P 395681-58-0P 395681-60-4P
395681-62-6P 395681-64-8P 395681-65-9P 395681-66-0P
395681-68-2P 395681-69-3P 395681-71-7P 395681-73-9P
395681-74-0P 395681-75-1P 395681-77-3P 395681-79-5P
395681-80-8P 395681-82-0P 395681-84-2P 395681-86-4P
395681-88-6P 395681-90-0P 395681-92-2P 395681-94-4P
395681-96-6P
RL: IMF (Industrial manufacture); POF (Polymer in formulation);
TEM (Technical or engineered material use); PREP (Preparation);
USES (Uses)
(colored resin emulsions for ink-jet printing inks,
electrocoating fluids and color filters)
REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS AVAILABLE
IN THE RE FORMAT

L31 ANSWER 16 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2002:98759 HCAPLUS Full-text
DOCUMENT NUMBER: 136:152807
TITLE: Weather-resistant anionic
electrodeposition coating materials
INVENTOR(S): Mizoguch, Yoshitaka; Aoki, Kenji
PATENT ASSIGNEE(S): Kansai Paint Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002038084	A	20020206	JP 2000-220236	2000 0721
			<--	
PRIORITY APPLN. INFO.:			JP 2000-220236	2000 0721
			<--	

ED Entered STN: 06 Feb 2002

AB Coating materials contain acrylic copolymers having acid value 20-200 mg KOH/g and OH value 20-200 mg KOH/g, amino resin hardeners, blocked polyisocyanate hardeners, UV absorbers, and light stabilizers. Thus, a coating material (8% solids) on anodically oxidized Al contained acrylic acid-Bu acrylate-Et acrylate-2-hydroxyethyl acrylate-2-(2'-hydroxy-5'-methacryloxyethylphenyl)-2H- benzotriazole-4-methacryloyloxy-1,2,2,6,6-pentamethylpiperidine-Me methacrylate-styrene copolymer triethylamine salt 7 (as copolymer), Cymel 300 2, Duranate 24A90CX 1, p-toluenesulfonic acid 0.05 kg, water, and triethylamine (to pH 8.0).

IT 394251-89-9DP, reaction products with blocked polyisocyanates and melamine resins 394251-92-4DP, reaction products with blocked polyisocyanates and melamine resins 394251-94-6DP, reaction products with blocked polyisocyanates and melamine resins 394251-96-8DP, reaction products with blocked polyisocyanates and melamine resins RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

RN 394251-89-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate and 2-propenoic acid, compd. with N,N-diethylethanamine (9CI) (CA INDEX NAME)

CM 1

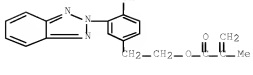
CRN 121-44-8
CMF C6 H15 N

CM 2

CRN 394251-88-8
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H4 O2)x
CCI PMS

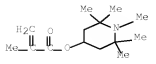
CM 3

CRN 96478-09-0
CMF C18 H17 N3 O3



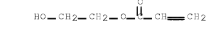
CM 4

CRN 68548-08-3
CMF C14 H25 N O2



CM 5

CRN 818-61-1
CMF C5 H8 O3

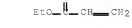


CM 6

CRN 141-32-2
CMF C7 H12 O2

CM 7

CRN 140-88-5
CMF C5 H8 O2



CM 8

CRN 100-42-5
CMF C8 H8

CM 9

CRN 80-62-6
CMF C5 H8 O2

CM 10

CRN 79-10-7
CMF C3 H4 O2

RN 394251-92-4 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
2-propenoic acid and 2,2,6,6-tetramethyl-4-piperidinyl
2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
(CA INDEX NAME)

CM 1

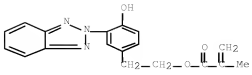
CRN 121-44-8
CMF C6 H15 N

CM 2

CRN 394251-91-3
CMF (C18 H17 N3 O3 . C13 H23 N O2 . C8 H8 . C7 H12 O2 . C5 H8 O3
. C5 H8 O2 . C5 H8 O2 . C3 H4 O2)x
CCI PMS

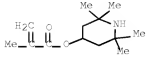
CM 3

CRN 96478-09-0
CMF C18 H17 N3 O3



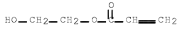
CM 4

CRN 31582-45-3
CMF C13 H23 N O2



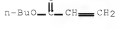
CM 5

CRN 818-61-1
CMF C5 H8 O3



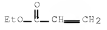
CM 6

CRN 141-32-2
CMF C7 H12 O2



CM 7

CRN 140-88-5
CMF C5 H8 O2



CM 8

CRN 100-42-5
CMF C8 H8

CM 9

CRN 80-62-6
CMF C5 H8 O2

CM 10

CRN 79-10-7
CMF C3 H4 O2

RN 394251-94-6 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate,
2-propenoic acid and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)
(CA INDEX NAME)

CM 1

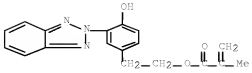
CRN 121-44-8
CMF C6 H15 N

CM 2

CRN 328404-57-5
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C10 H20 O5 Si . C8 H8 . C7
H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H4 O2)x
CCI PMS

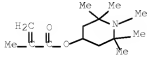
CM 3

CRN 96478-09-0
CMF C18 H17 N3 O3



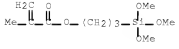
CM 4

CRN 68548-08-3
CMF C14 H25 N O2



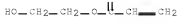
CM 5

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 6

CRN 818-61-1
CMF C5 H8 O3

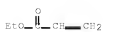


CM 7

CRN 141-32-2
CMF C7 H12 O2

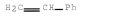
CM 8

CRN 140-88-5
CMF C5 H8 O2



CM 9

CRN 100-42-5
CMF C8 H8

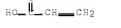


CM 10

CRN 80-62-6
CMF C5 H8 O2

CM 11

CRN 79-10-7
CMF C3 H4 O2



RN 394251-96-8 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
2-propenoic acid, 2,2,6,6-tetramethyl-4-piperidinyl
2-methyl-2-propenoate and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate, compd. with N,N-diethylethanamine (9CI)

(CA INDEX NAME)

CM 1

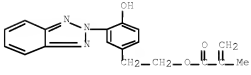
CRN 121-44-8
CMF C6 H15 N

CM 2

CRN 394251-95-7
CMF (C18 H17 N3 O3 . C13 H23 N O2 . C10 H20 O5 Si . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C5 H8 O2 . C3 H4 O2)x
CCI PMS

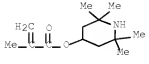
CM 3

CRN 96478-09-0
CMF C18 H17 N3 O3



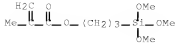
CM 4

CRN 31582-45-3
CMF C13 H23 N O2



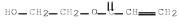
CM 5

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 6

CRN 818-61-1
CMF C5 H8 O3

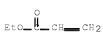


CM 7

CRN 141-32-2
CMF C7 H12 O2

CM 8

CRN 140-88-5
CMF C5 H8 O2



CM 9

CRN 100-42-5
CMF C8 H8

CM 10

CRN 80-62-6
CMF C5 H8 O2

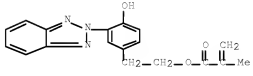
CM 11

CRN 79-10-7
CMF C3 H4 O2

IT 328404-57-5P 394251-88-8P 394251-91-3P
394251-95-7P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
RN 328404-57-5 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate, 2-propenoic acid and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

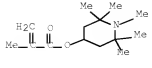
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



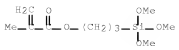
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



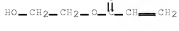
CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 4

CRN 818-61-1
CMF C5 H8 O3

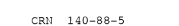


CM 5

CRN 141-32-2
CMF C7 H12 O2

CM 6

CRN 140-88-5
CMF C5 H8 O2



CM 7

CRN 100-42-5
CMF C8 H8

CM 8

CRN 80-62-6
CMF C5 H8 O2

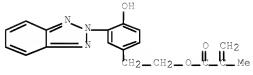
CM 9

CRN 79-10-7
CMF C3 H4 O2

RN 394251-88-8 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate and
2-propenoic acid (9CI) (CA INDEX NAME)

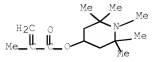
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 68548-08-3
CMF C14 H25 N O2

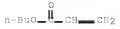


CM 3

CRN 818-61-1
CMF C5 H8 O3

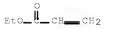
CM 4

CRN 141-32-2
CMF C7 H12 O2



CM 5

CRN 140-88-5
CMF C5 H8 O2



CM 6

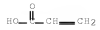
CRN 100-42-5
CMF C8 H8

CM 7

CRN 80-62-6
CMF C5 H8 O2

CM 8

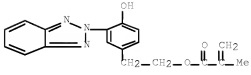
CRN 79-10-7
CMF C3 H4 O2



RN 394251-91-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
2-propenoic acid and 2,2,6,6-tetramethyl-4-piperidinyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

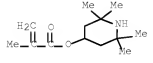
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



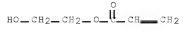
CM 2

CRN 31582-45-3
CMF C13 H23 N O2



CM 3

CRN 818-61-1
CMF C5 H8 O3

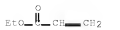


CM 4

CRN 141-32-2
CMF C7 H12 O2

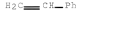
CM 5

CRN 140-88-5
CMF C5 H8 O2



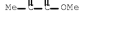
CM 6

CRN 100-42-5
CMF C8 H8



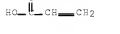
CM 7

CRN 80-62-6
CMF C5 H8 O2



CM 8

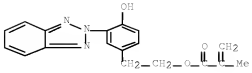
CRN 79-10-7
CMF C3 H4 O2



RN 394251-95-7 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate,
2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate,
2-propenoic acid, 2,2,6,6-tetramethyl-4-piperidinyl
2-methyl-2-propenoate and 3-(trimethoxysilyl)propyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

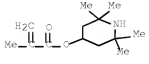
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



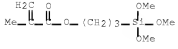
CM 2

CRN 31582-45-3
CMF C13 H23 N O2



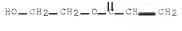
CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si



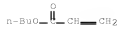
CM 4

CRN 818-61-1
CMF C5 H8 O3



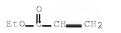
CM 5

CRN 141-32-2
CMF C7 H12 O2



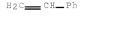
CM 6

CRN 140-88-5
CMF C5 H8 O2



CM 7

CRN 100-42-5
CMF C8 H8

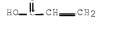


CM 8

CRN 80-62-6
CMF C5 H8 O2

CM 9

CRN 79-10-7
CMF C3 H4 O2



IC ICM C09D175-04
ICS C09D005-44; C09D133-00; C09D161-20
CC 42-7 (Coatings, Inks, and Related Products)
Section cross-reference(s): 56
ST weather resistant anionic electrodeposition coating material; acrylic melamine electrodeposition coating light stabilizer; UV absorber acrylic melamine electrodeposition coating

IT Electrodeposits
(anionic; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT Amines, uses
RL: MOA (Modifier or additive use); USES (Uses)
(hindered; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT Vinyl compounds, uses
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymers; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT Polymerization
(radical; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT Aminoplasts
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(reaction products with acrylic resins and blocked polyisocyanates, Cymel 300 and Nikalac MX 430; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT Aminoplasts
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(reaction products with acrylic resins and blocked polyisocyanates; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT Crosslinking agents
Crosslinking catalysts
UV stabilizers
(weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT Coating materials
(weather-resistant; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT 9003-08-1DP, Cymel 300, reaction products with acrylic resins and blocked polyisocyanates
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(Cymel 300 and Nikalac MX 430; weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT 104-15-4, p-Toluenesulfonic acid, uses
RL: CAT (Catalyst use); USES (Uses)
(weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)
IT 822-06-0DP, Hexamethylene diisocyanate, derivs., reaction products with acrylic resins and melamine resins 73928-87-7DP, Duranate 24A90CX, reaction products with acrylic resins and melamine resins 394251-89-9DP, reaction products with blocked polyisocyanates and melamine resins 394251-92-4DP, reaction products with blocked polyisocyanates and melamine resins 394251-94-6DP, reaction products with blocked polyisocyanates and melamine resins 394251-96-8DP,

reaction products with blocked polyisocyanates and melamine resins
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

IT 328404-57-5P 394251-88-8P 394251-91-3P 394251-95-7P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(weather-resistant anionic electrodeposition coating materials containing acrylic resins and melamine resins and light stabilizers)

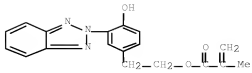
L31 ANSWER 17 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2001:864997 HCAPLUS Full-text
DOCUMENT NUMBER: 136:14033
TITLE: Electrically conductive pastes and optical semiconductor devices manufactured by using them with excellent UV and weather resistance
INVENTOR(S): Shizuki, Hironori
PATENT ASSIGNEE(S): Toshiba Chemical Corp., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001332124	A	20011130	JP 2000-149863	2000 0522
			<--	
PRIORITY APPLN. INFO.:			JP 2000-149863	2000 0522
			<--	

ED Entered STN: 30 Nov 2001
AB The pastes, useful for bonding blue LED chips to lead frames, contain organic binders, solvents and/or monomers, Ag-containing elec. conductive powders, and 0.1-10% (based on resin solids content) compds. having ≥1 benzotriazole structures and methacryloyl or hydroxyethyl groups. The compds. may be copolymd. with the monomers in advance. The powders may contain 5-20% TiO2.
IT 153175-43-0, 2-(2'-Hydroxy-5'-methacryloxyethylphenyl)-2H-benzotriazole-methyl methacrylate copolymer
RL: MOA (Modifier or additive use); USES (Uses)
(UV absorber; elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)
RN 153175-43-0 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with methyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 80-62-6
CMF C5 H8 O2

IC ICM H01B001-22
ICS C08K003-08; C08K003-22; C08K005-00; C08K005-3472; C08L101-00; C09J004-06; H01L021-52; H05K003-32; C09J009-02; C09J011-04; C09J011-06; C09J201-00; C08L033-14
CC 76-3 (Electric Phenomena)
Section cross-reference(s): 38, 73
ST elec conductive paste silver weather resistance; UV resistance epoxy paste optical semiconductor; benzotriazole UV absorber titania paste LED
IT Epoxy resins, uses
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinked, binder; elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)
IT Electrically conductive pastes
Electroluminescent devices
Optoelectronic semiconductor devices
UV stabilizers
(elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)
IT Phenolic resins, uses
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(epoxy, binder; elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)
IT Epoxy resins, uses
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(phenolic, binder; elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)
IT 153175-43-0, 2-(2'-Hydroxy-5'-methacryloxyethylphenyl)-2H-benzotriazole-methyl methacrylate copolymer 196516-61-7
RL: MOA (Modifier or additive use); USES (Uses)
(UV absorber; elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)
IT 373599-19-0P, Celloxide 2021-GT 302-PG 207S-YL 983U copolymer 376366-31-3P, BRG 558-EOCN 103S-Epikote 1007 copolymer
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(binder; elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)

IT 7440-22-4, Silver, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)

IT 13463-67-7, Titanium oxide, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(rutile-type; elec. conductive pastes containing benzotriazole compds. for optical semiconductor devices with good UV and weather resistance)

L31 ANSWER 18 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2001:563988 HCAPLUS Full-text
DOCUMENT NUMBER: 135:159968
TITLE: Electrochromic component
INVENTOR(S): Asano, Takeshi; Oshima, Shinji; Nishikitani, Yoshinori
PATENT ASSIGNEE(S): Nisseki Mitsubishi Oil Corporation, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 22 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

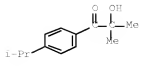
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001209078	A	20010803	JP 2000-16929	2000 0126
			<--	
WO 2001055784	A1	20010802	WO 2001-JP455	2001 0124
			<--	
W: US				
RW: DE, FR, GB				
US 20030072071	A1	20030417	US 2002-205982	2002 0726
			<--	
US 6728022	B2	20040427		
PRIORITY APPLN. INFO.:			JP 2000-16929 A	2000 0126
			<--	
			WO 2001-JP455 A1	2001 0124
			<--	

ED Entered STN: 03 Aug 2001
AB The invention refers to a electrochromic device comprising an electrochromic polymer and an organic compound with bipyridinium ion as an cathodic electrochromic structure, and a metallocene as a anodic electrochromic structure, wherein the organic compound may react with the polymer.
IT 352427-38-4
RL: DEV (Device component use); USES (Uses)
(electrochromic component)
RN 352427-38-4 HCAPLUS
CN 1-Propanone, 2-hydroxy-2-methyl-1-[4-(1-methylethyl)phenyl]-, polymer with 2-(2H-benzotriazol-2-yl)-4-(1,1-dimethylethyl)phenol and α-(2-methyl-1-oxo-2-propenyl)-ω-methoxypoly(oxy-

1,2-ethanediyl) (9CI) (CA INDEX NAME)

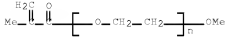
CM 1

CRN 69673-85-4
CMF C13 H18 O2



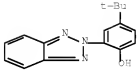
CM 2

CRN 26915-72-0
CMF (C2 H4 O)n C5 H8 O2
CCI PMS



CM 3

CRN 3147-76-0
CMF C16 H17 N3 O



IC ICM G02F001-15
ICS B60R001-04; C08F008-30; C08F008-42; C09K009-02
CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
IT 1332-29-2, Tin oxide 2440-22-4, 2-(5-Methyl-2-hydroxyphenyl)benzotriazole 7440-05-3, Palladium, uses 16731-68-3, 2-Undecylimidazole 50926-11-9, ITO 352427-34-0 352427-35-1 352427-37-3 352427-38-4 352427-39-5 352427-40-8 352427-41-9 352427-43-1 352430-76-3
RL: DEV (Device component use); USES (Uses)
(electrochromic component)

L31 ANSWER 19 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2001:324518 HCAPLUS Full-text
DOCUMENT NUMBER: 134:341657
TITLE: Water-soluble electrodeposition coating compositions with good weather

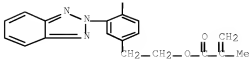
resistance
INVENTOR(S): Obata, Katsuya; Kishida, Katsuhiko
PATENT ASSIGNEE(S): Honey Kasei K. K., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001123107	A	20010508	JP 1999-338316	1999 1025
			<--	
PRIORITY APPLN. INFO.:			JP 1999-338316	1999 1025
			<--	

ED Entered STN: 08 May 2001
AB The compns. contain (A) 100 parts (meth)acrylic polymers prepared from UV-absorbing vinyl monomers 1-20, radical-scavenging vinyl monomers 1-20, F-containing vinyl monomers 1-15, CO2H-containing vinyl monomers 3-15, OH-containing vinyl monomers 5-30, and (meth)acrylates 0-89 parts and (B) 10-100 parts amino resins. Thus, an aqueous solution containing 6:15:10:18:26:10:10:5 acrylic acid-2-hydroxyethyl acrylate-styrene-Bu acrylate-Me methacrylate-RUVA 93 [2-(2'-hydroxy-5'-methacryloxyethylphenyl)-2H-benzotriazole]- 1,2,2,6,6-pentamethyl-4-piperidyl methacrylate-Famac (2-perfluorooctylethyl methacrylate) copolymer, Cymel 235 (melamine resin), and dimethylaminoethanol was electrodeposited on an Al plate to give a coating showing gloss 85% and gloss retention 100% after 3 cycles of accelerated weathering tests.
IT 338405-66-6P, Acrylic acid-butyl acrylate-2-hydroxyethyl acrylate-methyl methacrylate-1,2,2,6,6-pentamethyl-4-piperidyl methacrylate-2-perfluorooctylethyl methacrylate-RUVA 93-styrene copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
(water-thinned electrodeposition coatings with good weather resistance)
RN 338405-66-6 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate and 2-propenoic acid (9CI) (CA INDEX NAME)

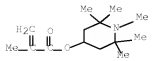
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



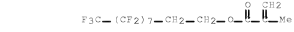
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



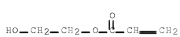
CM 3

CRN 1996-88-9
CMF C14 H9 F17 O2



CM 4

CRN 818-61-1
CMF C5 H8 O3



CM 5

CRN 141-32-2
CMF C7 H12 O2

CM 6

CRN 100-42-5
CMF C8 H8

CM 7

CRN 80-62-6
CMF C5 H8 O2

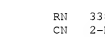
CM 8

CRN 79-10-7
CMF C3 H4 O2

IT 338405-70-2P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(water-thinned electrodeposition coatings with good weather resistance)
RN 338405-70-2 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, formaldehyde, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate, 2-propenoic acid and 1,3,5-triazine-2,4,6-triamine, compd. with 2-(dimethylamino)ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 108-01-0
CMF C4 H11 N O

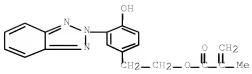


CM 2

CRN 338405-69-9
CMF (C18 H17 N3 O3 . C14 H25 N O2 . C14 H9 F17 O2 . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C3 H6 N6 . C3 H4 O2 . C H2 O)x
CCI PMS

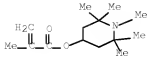
CM 3

CRN 96478-09-0
CMF C18 H17 N3 O3



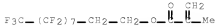
CM 4

CRN 68548-08-3
CMF C14 H25 N O2



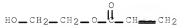
CM 5

CRN 1996-88-9
CMF C14 H9 F17 O2



CM 6

CRN 818-61-1
CMF C5 H8 O3

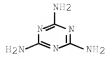


CM 7

CRN 141-32-2
CMF C7 H12 O2

CM 8

CRN 108-78-1
CMF C3 H6 N6



CM 9

CRN 100-42-5
CMF C8 H8

CM 10

CRN 80-62-6
CMF C5 H8 O2

CM 11

CRN 79-10-7
CMF C3 H4 O2

CM 12

CRN 50-00-0
CMF C H2 O

IC ICM C09D157-08

ICS C09D005-44; C09D157-10; C09D161-20
CC 42-7 (Coatings, Inks, and Related Products)
ST electrodeposition acrylic coating aminoplast crosslinked weatherability; melamine resin crosslinked acrylic electrodeposition coating; methylaminoethanol salt acrylic polymer aminoplast electrodeposit
IT Aminoplasts
RL: POF (Polymer in formulation); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)
(crosslinking agents; water-thinned electrodeposition coatings with good weather resistance)
IT Coating materials
(water-soluble; water-thinned electrodeposition coatings with good weather resistance)
IT Electrodeposits
(water-thinned electrodeposition coatings with good weather resistance)
IT Coating materials
(weather-resistant; water-thinned electrodeposition coatings with good weather resistance)
IT 338405-66-8P, Acrylic acid-butyl acrylate-2-hydroxyethyl acrylate-methyl methacrylate-1,2,2,6,6-pentamethyl-4-piperidyl methacrylate-2-perfluorooctylethyl methacrylate-RUVA 93-styrene copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
(water-thinned electrodeposition coatings with good weather resistance)
IT 338405-70-2P
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(water-thinned electrodeposition coatings with good weather resistance)

L31 ANSWER 20 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2001:174226 HCAPLUS Full-text
DOCUMENT NUMBER: 134:209402
TITLE: Acrylic polymer-based anionic electrodeposition compositions
INVENTOR(S): Yokoyama, Tetsuya; Kamikado, Koji; Hirano, Koji; Mizoguch, Yoshitaka
PATENT ASSIGNEE(S): Kansai Paint Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001064568	A	20010313	JP 1999-238166	1999 0825
			<--	
PRIORITY APPLN. INFO.:			JP 1999-238166	1999 0825
			<--	

ED Entered STN: 14 Mar 2001
AB The title compns., giving coated products with good appearance and weather resistance, comprise (a) water-dispersible vinyl copolymers having alkoxy silyl groups on the side chains (e.g., acrylic acid-Bu acrylate-Et acrylate-2-hydroxyethyl acrylate-γ-methacryloxypropyltrimethoxysilane-Me methacrylate-styrene copolymer) or having alkoxy

silyl monomers containing benzotriazole- and/or hindered amino-containing acrylic monomers (e.g., acrylic acid-Bu acrylate-Et acrylate-FA 711MM-2-hydroxyethyl acrylate-γ-methacryloxypropyltrimethoxysilane-Me methacrylate-RUVA 93-styrene copolymer) with acid-value 15-150 mg-KOH/g and OH-value 30-200 mg-KOH/g 40-84, (b) vinyl copolymers containing benzotriazole- and/or hindered amino-containing acrylic monomers with acid-value <14 mg-KOH/g (e.g., Bu acrylate-Bu methacrylate-2-ethylhexyl methacrylate-FA 711MM-2-hydroxyethyl methacrylate-RUVA 93 copolymer) 0.1-20, and (c) crosslinking agents (e.g., melamine resin) 15-50%, providing SP value of (b) is 0.3-1.5 smaller than that of (a).

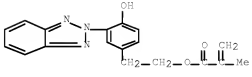
IT 328404-57-5 328404-59-7 328404-61-1
328404-63-3
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(acrylic polymer-based anionic electrodeposition compns.)

RN 328404-57-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-propenoate, ethenylbenzene, ethyl 2-propenoate, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate, 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate, 2-propenoic acid and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

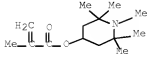
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 68548-08-3
CMF C14 H25 N O2

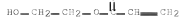


CM 3

CRN 2530-85-0
CMF C10 H20 O5 Si

CM 4

CRN 818-61-1
CMF C5 H8 O3

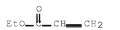


CM 5

CRN 141-32-2
CMF C7 H12 O2

CM 6

CRN 140-88-5
CMF C5 H8 O2



CM 7

CRN 100-42-5
CMF C8 H8

CM 8

CRN 80-62-6
CMF C5 H8 O2

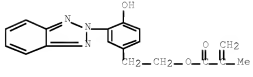
CM 9

CRN 79-10-7
CMF C3 H4 O2

RN 328404-59-7 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with butyl 2-methyl-2-propenoate, butyl 2-propenoate, 2-ethylhexyl 2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and 1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

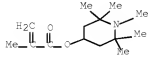
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



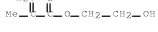
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



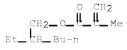
CM 3

CRN 868-77-9
CMF C6 H10 O3



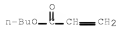
CM 4

CRN 688-84-6
CMF C12 H22 O2



CM 5

CRN 141-32-2
CMF C7 H12 O2



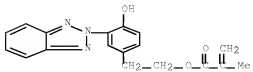
CM 6

CRN 97-88-1
CMF C8 H14 O2

RN 328404-61-1 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-methyl-2-propenoate, butyl 2-propenoate, 2-ethylhexyl
2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate,
methyl 2-methyl-2-propenoate and
1,2,2,6,6-pentamethyl-4-piperidinyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

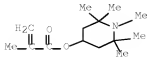
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



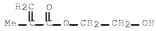
CM 2

CRN 68548-08-3
CMF C14 H25 N O2



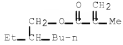
CM 3

CRN 868-77-9
CMF C6 H10 O3



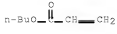
CM 4

CRN 688-84-6
CMF C12 H22 O2



CM 5

CRN 141-32-2
CMF C7 H12 O2



CM 6

CRN 97-88-1
CMF C8 H14 O2

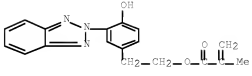
CM 7

CRN 80-62-6
CMF C5 H8 O2

RN 328404-63-3 HCAPLUS
CN 2-Propenoic acid, 2-methyl-,
2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer
with butyl 2-methyl-2-propenoate, butyl 2-propenoate, 2-ethylhexyl
2-methyl-2-propenoate, 2-hydroxyethyl 2-methyl-2-propenoate and
methyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

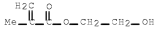
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



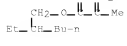
CM 2

CRN 868-77-9
CMF C6 H10 O3



CM 3

CRN 688-84-6
CMF C12 H22 O2



CM 4

CRN 141-32-2
CMF C7 H12 O2

CM 5

CRN 97-88-1
CMF C8 H14 O2

CM 6

CRN 80-62-6
CMF C5 H8 O2

IC ICM C09D133-00
ICS C09D005-44; C09D139-04; C09D161-28; C09D175-04
CC 42-7 (Coatings, Inks, and Related Products)
Section cross-reference(s): 76
ST acrylic polymer anionic electrodeposition weather resistance; appearance acrylic polymer anionic electrodeposition; benzotriazole acrylic polymer anionic electrodeposition; hindered amino acrylic polymer anionic electrodeposition
IT Electrodeposition
(acrylic polymer-based anionic electrodeposition compns.)
IT Aminoplasts
RL: MOA (Modifier or additive use); USES (Uses)
(crosslinking agents; acrylic polymer-based anionic electrodeposition compns.)
IT Crosslinking agents
(melamine resin; acrylic polymer-based anionic electrodeposition compns.)
IT Coating materials
(weather-resistant; acrylic polymer-based anionic electrodeposition compns.)
IT 92598-34-0 328404-57-5 328404-59-7
328404-61-1 328404-63-3
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(acrylic polymer-based anionic electrodeposition

compns.)
IT 9003-08-1, Melamine resin
RL: MOA (Modifier or additive use); USES (Uses)
(crosslinking agents; acrylic polymer-based anionic electrodeposition compns.)

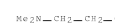
L31 ANSWER 21 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 2000:181094 HCAPLUS Full-text
DOCUMENT NUMBER: 132:209229
TITLE: Aqueous acrylic electrodeposition coating compositions with storage stability and weather resistance
INVENTOR(S): Sauchi, Yasuyuki; Ishii, Hiroaki; Kayamori, Satoshi
PATENT ASSIGNEE(S): Toa Gosei Chemical Industry Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 8 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000080310	A	20000321	JP 1998-265762	1998 0904 <--
PRIORITY APPLN. INFO.:			JP 1998-265762	1998 0904 <--

ED Entered STN: 21 Mar 2000
AB Title compns., useful for Al substrates, contain aminoplasts and (partially) neutralized acrylic polymers prepared from alkyl (meth)acrylates, COOH-containing vinyl compds., OH-containing vinyl compds., UV-absorbing vinyl compds. and other monomers. An aqueous composition containing acrylic acid-styrene-Bu acrylate-2-hydroxyethyl acrylate-methacrylic acid-Me methacrylate-RUVA 93 copolymer, Cymel 235, organic Al compds., and dimethylethanolamine showed good storage stability at room temperature for 3 days and was electrodeposited on an Al plate to form a film with gloss retention 82.4% after 4,000 h under sunshine weatherometer.
IT 260389-73-9P, Acrylic acid-butyl acrylate-2-hydroxyethyl acrylate-methacrylic acid-methyl methacrylate-RUVA 93-styrene copolymer dimethylethanolamine salt
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(UV-absorbing acrylic resin-based aqueous electrodeposition coatings with storage stability and weather resistance)
RN 260389-73-9 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, polymer with 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl 2-methyl-2-propenoate, butyl 2-propenoate, ethenylbenzene, 2-hydroxyethyl 2-propenoate, methyl 2-methyl-2-propenoate and 2-propenoic acid, compd. with 2-(dimethylamino)ethanol (9CI) (CA INDEX NAME)

CM 1

CRN 108-01-0
CMF C4 H11 N O

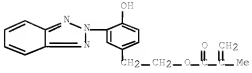


CM 2

CRN 260389-72-8
CMF (C18 H17 N3 O3 . C8 H8 . C7 H12 O2 . C5 H8 O3 . C5 H8 O2 . C4 H6 O2 . C3 H4 O2)x
CCI PMS

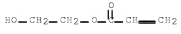
CM 3

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 4

CRN 818-61-1
CMF C5 H8 O3



CM 5

CRN 141-32-2
CMF C7 H12 O2

CM 6

CRN 100-42-5
CMF C8 H8

CM 7

CRN 80-62-6
CMF C5 H8 O2

CM 8

CRN 79-41-4
CMF C4 H6 O2

CM 9

CRN 79-10-7
CMF C3 H4 O2

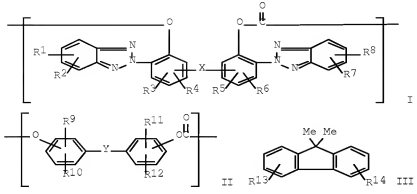
IC ICM C09D005-44
ICS C09D133-06; C09D133-14; C09D139-04; C09D161-20
CC 42-7 (Coatings, Inks, and Related Products)
Section cross-reference(s): 56
ST aq acrylic electrodeposition coating storage stability; weather resistance aq acrylic electrodeposition coating; UV absorbing methacrylate polymer aq electrodeposition coating
IT Electrodeposits
(UV-absorbing acrylic resin-based aqueous electrodeposition coatings with storage stability and weather resistance)
IT Acrylic polymers, uses
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(UV-absorbing acrylic resin-based aqueous electrodeposition coatings with storage stability and weather resistance)
IT Aminoplasts
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(UV-absorbing acrylic resin-based aqueous electrodeposition coatings with storage stability and weather resistance)
IT Windows
(frames, Al-made, as substrates; UV-absorbing acrylic resin-based aqueous electrodeposition coatings with storage stability and weather resistance)
IT 260389-73-9P, Acrylic acid-butyl acrylate-2-hydroxyethyl acrylate-methacrylic acid-methyl methacrylate-RUVA 93-styrene

copolymer dimethylethanolamine salt
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(UV-absorbing acrylic resin-based aqueous electrodeposition coatings with storage stability and weather resistance)
IT 9003-08-1, Cymel 235
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(UV-absorbing acrylic resin-based aqueous electrodeposition coatings with storage stability and weather resistance)
IT 7429-90-5, Aluminum, miscellaneous
RL: MSC (Miscellaneous)
(substrates; UV-absorbing acrylic resin-based aqueous electrodeposition coatings with storage stability and weather resistance)

L31 ANSWER 22 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1998:685250 HCAPLUS Full-text
DOCUMENT NUMBER: 130:8862
TITLE: Electrophotographic photoreceptor containing aromatic polycarbonate and electrophotographic apparatus
INVENTOR(S): Takekawa, Ichiro; Nukata, Hidemi; Nakamura, Hiroshi; Miyamoto, Masakiko
PATENT ASSIGNEE(S): Fuji Xerox Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 27 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10282690	A	19981023	JP 1997-88379	1997 0407
			<--	
PRIORITY APPLN. INFO.:			JP 1997-88379	1997 0407
			<--	

OTHER SOURCE(S): MARPAT 130:8862
ED Entered STN: 29 Oct 1998
GI



I

II

III

AB The title photoreceptor comprises a conductive support coated with a photosensitive layer containing a polycarbonate copolymer resin having repeating units I and II [R1-12 = H, halo, C1-5 alkyl, C6-12 aryl, C2-5 alkenyl, C1-5 alkoxy, C7-17 aralkyl (these groups may be substituted by C1-5 alkyl, C1-5 alkenyl, C1-5 alkoxy, halo, or dimethylpolysiloxy group); X = O(CH2O)a, (CH2O)aCO2(CH2)bOCO(CH2)c, (CH2)a, (CH2)aCO(CH2)bCO(CH2)c, OCOCH:CHC6H4-p-CH:CHCO2, CH2CONHC6H4CONHCH2 (a, b, c = 0-20); Y = (CR13R14)c(CH2)d(CR15R16)e, S, SO2, O, (CH2)f(SiR13R14O)gSiR13R14(CH2)f, III, CR13R14C6H4CR15R16, 1,1-cyclohexyl, CMe2; R13-16 = H, halo, C1-5 alkyl, C6-12 aryl, C2-5 alkenyl, C1-5 alkoxy, C7-17 aralkyl (these groups may be substituted by C1-5 alkyl, C1-5 alkenyl, C1-5 alkoxy, halo, or dimethylpolysiloxy group); c, e, f = 0-20; d, g = 1-100] and a triphenylamine compound An electrophotog. apparatus using the photoreceptor is also claimed. The photoreceptor shows high abrasion resistance and durability in repeated use and provides high quality images without fog and black spot.

IT 192209-77-1 215809-90-8 215810-06-3

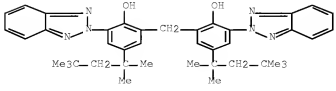
RL: DEV (Device component use); USES (Uses)
(electrophotog. apparatus having photoreceptor containing polycarbonate and triphenylamine)

RN 192209-77-1 HCAPLUS

CN Carbonic acid, polymer with 2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-tetramethylbutyl)phenol] and 4,4'-(1-methylethylidene)bis[phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 103597-45-1
CMF C41 H50 N6 O2

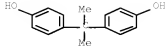


CM 2

CRN 463-79-6
CMF C H2 O3

CM 3

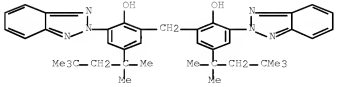
CRN 80-05-7
CMF C15 H16 O2



RN 215809-90-8 HCAPLUS
CN Carbonic acid, polymer with 4,4'-cyclohexylidenebis[phenol] and 2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-tetramethylbutyl)phenol] (9CI) (CA INDEX NAME)

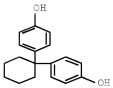
CM 1

CRN 103597-45-1
CMF C41 H50 N6 O2



CM 2

CRN 843-55-0
CMF C18 H20 O2



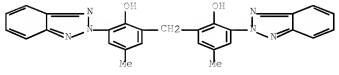
CM 3

CRN 463-79-6
CMF C H2 O3

RN 215810-06-3 HCAPLUS
CN Carbonic acid, polymer with
2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-methylphenol] and
4,4'-(1-methylethylidene)bis[phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 30653-05-5
CMF C27 H22 N6 O2

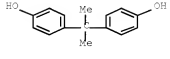


CM 2

CRN 463-79-6
CMF C H2 O3

CM 3

CRN 80-05-7
CMF C15 H16 O2



IC ICM G03G005-05
ICS C08G064-12; C08K005-17; C08L069-00; G03G005-06
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and
Other Reprographic Processes)
ST arom polycarbonate phenylamine electrophotog
photoreceptor app
IT Electrophotographic apparatus
Electrophotographic photoconductors (
photoreceptors)

(electrophotog. apparatus having photoreceptor containing polycarbonate and triphenylamine)
IT 65181-78-4, N,N'-Diphenyl-N,N'-bis(3-methylphenyl)-(1,1'-biphenyl)-4,4'-diamine 105465-13-2 111153-52-7 165320-08-1
RL: DEV (Device component use); USES (Uses)
(charge transporter; electrophotog. apparatus having photoreceptor containing polycarbonate and triphenylamine)
IT 192209-77-1 215809-90-8 215810-06-3
RL: DEV (Device component use); USES (Uses)
(electrophotog. apparatus having photoreceptor containing polycarbonate and triphenylamine)

L31 ANSWER 23 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1998:402375 HCAPLUS Full-text
DOCUMENT NUMBER: 129:96382
ORIGINAL REFERENCE NO.: 129:19872h,19873a
TITLE: UV-protected syndiotactic polystyrene overlay films
INVENTOR(S): Ojeda, Jaime R.
PATENT ASSIGNEE(S): Minnesota Mining and Manufacturing Co., USA
SOURCE: PCT Int. Appl., 35 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9825763	A1	19980618	WO 1997-US6992	1997 0425
			<--	
W: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, GH, HU, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, UZ, VN, YU				
RW: GH, KE, LS, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG				
US 5981076	A	19991109	US 1996-761912	1996 1209
			<--	
CA 2274774	C	19980618	CA 1997-2274774	1997 0425
			<--	
CA 2274774	A1	19980618		
AU 9729926	A	19980703	AU 1997-29926	1997 0425
			<--	
EP 942830	A1	19990922	EP 1997-924524	1997 0425
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EP 942830	B1	20030625		
R: DE, FR, GB, IT				
CN 1244156	A	20000209	CN 1997-181241	1997 0425
			<--	
CN 1096939	C	20021225		
JP 2001505835	T	20010508	JP 1998-526610	

1997
0425
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JP 4060371 B2 20080312
US 6120901 A 20000919 US 1998-98965
1998
0618
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KR 2000057453 A 20000915 KR 1999-705086
1999
0608
<--
JP 2007045158 A 20070222 JP 2006-242850
2006
0907
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PRIORITY APPLN. INFO.: US 1996-761912 A
1996
1209
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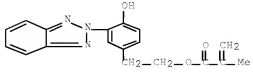
JP 1998-526610 A3
1997
0425
<--
WO 1997-US6992 W
1997
0425
<--
ED Entered STN: 01 Jul 1998
AB The film, having good dimensional stability, comprises a 1st layer comprising syndiotactic polystyrene and a 2nd layer comprising a UV-blocking material, optionally, PMMA, and optionally, a bonding and a 3rd layer disposed between the 1st and 2nd layers. Thus, coating Sorbalite OU (UV-ray resistant aqueous polyurethane) containing Triton TX 100 latex solution (solid content 15.6%) on a syndiotactic p-methylstyrene-styrene copolymer film gave a coated film with good UV-ray resistance.
IT 209329-55-5 209329-56-6
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(UV-blocking material; UV-protected syndiotactic polystyrene overlay films)
RN 209329-55-5 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with methyl 2-methyl-2-propenoate, 2-propenoic acid and 3-(trimethoxysilyl)propyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 4369-14-6
CMF C9 H18 O5 Si

CM 3

CRN 80-62-6
CMF C5 H8 O2

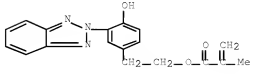
CM 4

CRN 79-10-7
CMF C3 H4 O2

RN 209329-56-6 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-[3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl]ethyl ester, polymer with 2-propenoic acid and 3-(trimethoxysilyl)propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

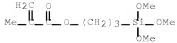
CM 1

CRN 96478-09-0
CMF C18 H17 N3 O3



CM 2

CRN 2530-85-0
CMF C10 H20 O5 Si



CM 3

CRN 79-10-7
CMF C3 H4 O2

IC ICM B32B027-28
ICS B32B027-18; C08K003-22; C08K005-132; C08K005-3475
CC 38-3 (Plastics Fabrication and Uses)
IT Electrode reaction
(photochem.; UV-protected syndiotactic polystyrene overlay films)
IT 79-10-7D, 2-Propenoic acid, polymers, uses 9002-84-0, PTFE 9011-14-7, PMMA 9017-68-9, Acrylic acid-isooctyl acrylate copolymer 57460-65-8, Ethyl acrylate-isopropenyloxazoline-methyl methacrylate copolymer 209329-55-5 209329-56-6 209534-17-8, Sorbalite OU
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(UV-blocking material; UV-protected syndiotactic polystyrene overlay films)
REFERENCE COUNT: 12 THERE ARE 12 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L31 ANSWER 24 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1998:352206 HCAPLUS Full-text
DOCUMENT NUMBER: 129:82813
ORIGINAL REFERENCE NO.: 129:17079a
TITLE: Electrodeposition coating compositions having excellent resistance to corrosion, hot water, and weather
INVENTOR(S): Tanimoto, Motoki; Inoue, Tsuyoshi
PATENT ASSIGNEE(S): Nippon Paint Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10147734	A	19980602	JP 1996-306665	1996 1118
			<--	
PRIORITY APPLN. INFO.:			JP 1996-306665	1996 1118
			<--	

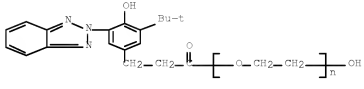
ED Entered STN: 10 Jun 1998

AB The coating compns. contain (A) low mol.-weight polyols having primary OH and prepared by reacting (i) cycloaliph. epoxy resins with mol. weight 400-3000 and epoxy equiv 200-1500 with (ii) monocarboxylic acids, preferably benzoic acid (I), dimethylolpropionic acid, dimethylolbutanoic acid, or glycolic acid, and further reacting the remaining OH with (iii) ε-caprolactone (II) and (B) crosslinking agents. The coatings may contain (C) ionic polymer polyols with mol. weight 3000-200,000 and OH value 15-120 and (D) 0.5-10 parts (per A + B 100 parts) UV absorbers as optional components. The coatings are especially suitable for automobiles. Thus, 207.1 parts a polyol (solid 75%, prepared from Sun-Tohto ST 3000, bisphenol A, I, and II at ratio 921.6:228.0:237.9:399.0), 820.4 parts 170.0:90.0:250.0:317.0:37.0:136.0:92.6 glycidyl methacrylate-2-hydroxyethyl methacrylate-styrene-Et methacrylate-Bu acrylate-Bu methacrylate copolymer N-methylethanolamine salt (solid 70.7%), 392.9 parts a crosslinking agent (prepared from IPDI, 2-ethylhexanol, and trimethylolpropane at ratio 371.4:218.0:75.0), 20.0 parts Tinuvin 1130, 10.0 parts ADK Stab LA 62 were mixed, neutralized with 19.1 parts glacial AcOH, thinned with 1391.6 parts H2O, and further mixed with 130.4 parts pigment paste and 2484.5 parts H2O to give a .apprx.20%-solids cationic electrodeposition coating.

IT 104810-48-2, Tinuvin 1130
RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

RN 104810-48-2 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-ω-hydroxy- (CA INDEX NAME)



IC ICM C09D005-44
ICS C09D005-44; C09D005-32; C09D007-12; C09D133-02; C09D133-06; C09D167-04; C09D175-04

CC 42-9 (Coatings, Inks, and Related Products)

ST anticorrosive electrodeposition coating epoxy resin; storage stable epoxy resin electrodeposition coating; water resistance epoxy resin electrodeposition coating; cycloaliph epoxy resin monocarboxylic acid polyether; caprolactone cycloaliph epoxy resin polyether; hydrogenated bisphenol A epoxy resin coating; automobile coating epoxy resin anticorrosive electrodeposition

IT Coating materials
Coating materials
(anticorrosive, water-thinned; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT Polyurethanes, uses
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinking agent; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT Aminoplasts
RL: MOA (Modifier or additive use); PRP (Properties); TEM

(Technical or engineered material use); USES (Uses)
(crosslinking agent; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT Polyesters, uses
Polyesters, uses
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(epoxy; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT Epoxy resins, uses
Epoxy resins, uses
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polyester-; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT Coating materials
Coating materials
(water-resistant, water-thinned; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT Electrodeposits
UV stabilizers
(water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT Coating materials
Coating materials
(water-thinned, weather-resistant; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT 77-99-6DP, reaction products with 2-ethylhexanol and IPDI
104-76-7DP, 2-Ethylhexanol, reaction products with IPDI and trimethylolpropane 4098-71-9DP, reaction products with 2-ethylhexanol and trimethylolpropane
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinking agent; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT 9003-08-1, Cymel 235 118232-50-1, Coatax WE 804
RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(crosslinking agent; water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

IT 208987-38-6P, Butyl acrylate-butyl methacrylate-ethyl methacrylate-glycidyl methacrylate-2-hydroxyethyl methacrylate-styrene copolymer, N-methylethanolamine salt
208987-40-0P 208987-41-1P 208987-42-2P, Acrylamide-acrylic acid-butyl acrylate-butyl methacrylate-ethyl methacrylate-2-hydroxyethyl methacrylate-methacrylic acid-styrene copolymer 209113-45-1P 209113-46-2P 209225-21-8P
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

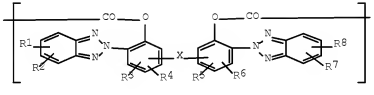
IT 104810-48-2, Tinuvin 1130 107119-91-5, ADK Stab LA 62
RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)

(water-thinned epoxy compns. for automobile electrodeposition coatings with corrosion, hot water and weather resistance)

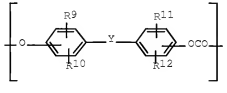
L31 ANSWER 25 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1997:139984 HCAPLUS Full-text
DOCUMENT NUMBER: 126:164198
ORIGINAL REFERENCE NO.: 126:31615a,31618a
TITLE: Copolycarbonate suitable for electrophotographic photoreceptor binder and its preparation
INVENTOR(S): Ogawa, Noryoshi; Tajima, Jun
PATENT ASSIGNEE(S): Mitsubishi Gas Chemical Co., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 08311193	A	19961126	JP 1995-122710	1995 0522
			<--	
JP 3460754	B2	20031027		
PRIORITY APPLN. INFO.:			JP 1995-122710	1995 0522
			<--	

ED Entered STN: 03 Mar 1997
GI



I



II

AB The title copolycarbonate has structural repeating units 1-60 mol.% I (R1-8 = H, F, Cl, Br, I, C1-5 alkyl, C6-12 aryl, C2-5 alkenyl, C1-5 alkoxy, C7-17 aralkyl; X = specified connection group) and II (R9-12 = H, F, Cl, Br, I, C1-5 alkyl, C6-12 aryl, C2-5 alkenyl, C1-5 alkoxy, C7-17 aralkyl; Y = specified connection group), wherein the copolycarbonate has a limiting viscosity of 0.30-2.00 dL/g. The copolycarbonate is prepared by polymerizing bisphenol derivs. and a carbonic compound The electrophotog . photoreceptor utilizing the copolycarbonate shows excellent durability.

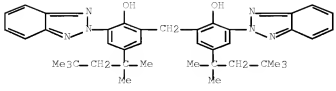
IT 135099-46-6P 135355-00-9P 159043-45-5P
159878-40-7P 186521-18-6P

RL: DEV (Device component use); PNU (Preparation, unclassified);
PREP (Preparation); USES (Uses)
(copolycarbonate suitable for electrophotog.
photoreceptor binder)

RN 135099-46-6 HCAPLUS
CN Carbonic dichloride, polymer with
2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-
tetramethylbutyl)phenol] and 4,4'-(1-methylethylidene)bis[phenol]
(9CI) (CA INDEX NAME)

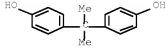
CM 1

CRN 103597-45-1
CMF C41 H50 N6 O2



CM 2

CRN 80-05-7
CMF C15 H16 O2



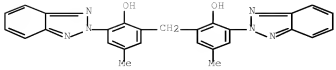
CM 3

CRN 75-44-5
CMF C C12 O

RN 135355-00-9 HCAPLUS
CN Carbonic dichloride, polymer with
2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-methylphenol] and
4,4'-(1-methylethylidene)bis[phenol] (9CI) (CA INDEX NAME)

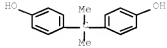
CM 1

CRN 30653-05-5
CMF C27 H22 N6 O2



CM 2

CRN 80-05-7
CMF C15 H16 O2



CM 3

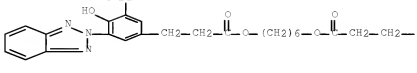
CRN 75-44-5
CMF C C12 O

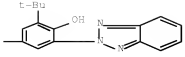
RN 159043-45-5 HCAPLUS
CN Benzenepropanoic acid, 3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, 1,6-hexanediyl ester, polymer with carbonic dichloride and 4,4'-(1-methylethylidene)bis[phenol] (9CI) (CA INDEX NAME)

CM 1

CRN 84268-08-6
CMF C44 H52 N6 O6

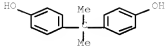
PAGE 1-A





CM 2

CRN 80-05-7
CMF C15 H16 O2



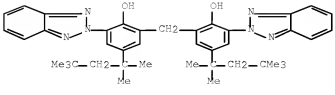
CM 3

CRN 75-44-5
CMF C C12 O

RN 159878-40-7 HCAPLUS
CN Carbonic dichloride, polymer with 4,4'-cyclohexylidenebis[phenol] and 2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-tetramethylbutyl)phenol] (9CI) (CA INDEX NAME)

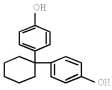
CM 1

CRN 103597-45-1
CMF C41 H50 N6 O2



CM 2

CRN 843-55-0
CMF C18 H20 O2



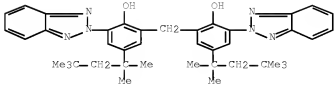
CM 3

CRN 75-44-5
CMF C Cl2 O

RN 186521-18-6 HCAPLUS
CN Carbonic dichloride, polymer with 2,2'-methylenebis[6-(2H-benzotriazol-2-yl)-4-(1,1,3,3-tetramethylbutyl)phenol] and 4,4'-(1-methylethylidene)bis[2-methylphenol] (9CI) (CA INDEX NAME)

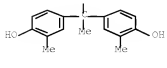
CM 1

CRN 103597-45-1
CMF C41 H50 N6 O2



CM 2

CRN 79-97-0
CMF C17 H20 O2



CM 3

CRN 75-44-5
CMF C C12 O

IC ICM C08G064-12
ICS C08G064-24; C08G064-30; C09D169-00; G03G005-05
CC 74-3 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35
ST copolycarbonate polycarbonate electrophotog photoreceptor binder
IT Electrophotographic photoconductors
(photoreceptors)
(binders; copolycarbonate suitable for electrophotog. photoreceptor binder and its preparation)
IT Polycarbonates, preparation
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(copolycarbonate suitable for electrophotog. photoreceptor binder)
IT 135099-46-5P 135355-00-9P 159043-45-5P 159878-40-7P 186521-18-6P
RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)
(copolycarbonate suitable for electrophotog. photoreceptor binder)

L31 ANSWER 26 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1995:833360 HCAPLUS Full-text
DOCUMENT NUMBER: 123:343570
ORIGINAL REFERENCE NO.: 123:61615a,61618a
TITLE: Anticorrosive weather- and hot water-resistant cationic electrodeposition coating compositions
INVENTOR(S): Tanimoto, Motoi; Tatsumi, Jinichi; Inoe, Tsuyoshi
PATENT ASSIGNEE(S): Nippon Paint Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 07166112	A	19950627	JP 1993-310751	1993 1210
PRIORITY APPLN. INFO.:			JP 1993-310751	1993 1210

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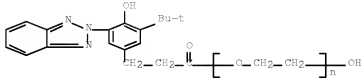
ED Entered STN: 05 Oct 1995
AB The title compns. contain acrylic resins having OH groups, tertiary amino groups, ester groups, and CO2H groups on side chains, 50.0-90.0, crosslinking agents 10.0-50.0, UV

light absorbers 0.4-10.0, and hindered amine-type light stabilizers 0.2-5.0%. Thus, a coating was obtained from acrylic resin [prepared from styrene-glycidyl methacrylate-2-hydroxyethyl methacrylate-Bu acrylate-Et methacrylate-Bu methacrylate-2-(methylamino)ethanol copolymer and 2.2 parts Rikacid HH-A] 700.0, crosslinking agent (prepared from IPDI, 2-ethylhexanol and trimethylolpropane) 300.0, Tinuvin 1130 (UV absorber) 20.0, ADK Stab LA-62 (hindered amine) 10.0, pigment paste 63.3 parts (as solid), AcOH, and H2O.

IT 104810-48-2, Tinuvin 1130
RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(UV absorber; anticorrosive weather- and hot water-resistant cationic electrodeposition coating compns.)

RN 104810-48-2 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-ω-hydroxy- (CA INDEX NAME)



IC ICM C09D005-44
ICS C09D133-06; C09D161-06; C09D175-04

CC 42-7 (Coatings, Inks, and Related Products)

ST cationic electrodeposition acrylic coating anticorrosive; urethann crosslinker acrylic electrophoretic coating; hindered amine light stabilizer coating; weather water resistance acrylic coating

IT Electrodeposits and Electroplates
(anticorrosive weather- and hot water-resistant cationic acrylic compns. for)

IT Phenolic resins, uses
RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(crosslinking agents; anticorrosive weather- and hot water-resistant cationic electrodeposition coating compns.)

IT Crosslinking agents
(for anticorrosive weather- and hot water-resistant cationic electrodeposition coating compns.)

IT Light stabilizers
(hindered amines; anticorrosive weather- and hot water-resistant cationic electrodeposition coating compns.)

IT Amines, uses
RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(hindered, light stabilizers; anticorrosive weather- and hot water-resistant cationic electrodeposition coating compns.)

IT 104810-48-2, Tinuvin 1130
RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(UV absorber; anticorrosive weather- and hot water-resistant cationic electrodeposition coating compns.)

IT 77-99-6DP, Trimethylolpropane, reaction products with 2-ethylhexanol and IPDI, copolymers with functional group-containing acrylic resins 80-62-6DP, Methyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with

blocked polyisocyanates 85-42-7DP, Rikacid HH-A, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 97-63-2DP, Ethyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 97-88-1DP, Butyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 100-42-5DP, Styrene, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 104-76-7DP, 2-Ethylhexanol, reaction products with IPDI and trimethylolpropane, copolymers with functional group-containing acrylic resins 106-91-2DP, Glycidyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 109-83-1DP, 2-(Methylamino)ethanol, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 141-32-2DP, Butyl acrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 868-77-9DP, 2-Hydroxyethyl methacrylate, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 4098-71-9DP, IPDI, reaction products with 2-ethylhexanol and trimethylolpropane, copolymers with functional group-containing acrylic resins 68548-08-3DP, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates 85099-10-1DP, Placcel FM 1, reaction products with functional group-containing (meth)acrylates, copolymers with blocked polyisocyanates
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(anticorrosive weather- and hot water-resistant cationic electrodeposition coating compns.)

IT 107119-91-5, ADK Stab LA 62
RL: MOA (Modifier or additive use); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(light stabilizer; anticorrosive weather- and hot water-resistant cationic electrodeposition coating compns.)

L31 ANSWER 27 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1994:325861 HCAPLUS Full-text
DOCUMENT NUMBER: 120:325861
ORIGINAL REFERENCE NO.: 120:57317a,57320a
TITLE: Cationic electrodeposition coating compositions
INVENTOR(S): Imai, Toshio; Shimomura, Kiichi; Tanaka, Takashi
PATENT ASSIGNEE(S): Nippon Oils & Fats Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 05320546	A	19931203	JP 1992-160409	19920527
			<--	
PRIORITY APPLN. INFO.:			JP 1992-160409	19920527
			<--	

ED Entered STN: 25 Jun 1994

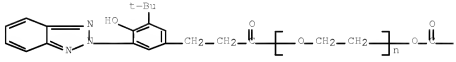
AB Title compns., effective for preventing UV-induced delamination when used as undercoats, comprise resins (as solid) 100, hydrophobic UV absorbers 0.2-10, and hindered amines 0.2-8 parts. Thus, a coating containing epoxy resin-amine reaction products 886, 2-[2-hydroxy-3,5-di(1,1-dimethylbenzyl)phenyl]benzotriazole 19, and bis(1-octyloxy-2,2,6,6-tetramethyl-4-piperidyl) sebacate 12 parts, and a pigment paste were applied electrophoretically and cured to form a 20 μm-thick film, which was coated with an acrylic-melamine topcoat with cross-cut adhesion 100/100 initially and also after 500-h accelerated weathering test.

IT 104810-47-1 104810-48-2
RL: USES (Uses)
(UV absorber, cationic electrodeposition undercoats containing hindered amines and, resistant to UV-induced delamination from topcoats)

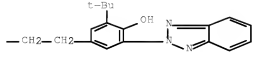
RN 104810-47-1 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-ω-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropoxy]- (CA INDEX NAME)

PAGE 1-A

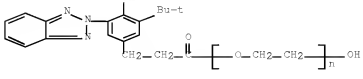


PAGE 1-B



RN 104810-48-2 HCAPLUS

CN Poly(oxy-1,2-ethanediyl), α-[3-[3-(2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxyphenyl]-1-oxopropyl]-ω-hydroxy- (CA INDEX NAME)



IC ICM C09D005-44

CC 42-7 (Coatings, Inks, and Related Products)

ST cationic electrodeposition undercoat delamination prevention; UV absorber cationic electrodeposition undercoat; hindered amine cationic electrodeposition undercoat

IT Electrodeposits and Electroplates
(cationic, containing hydrophobic UV absorbers and hindered amines,

undercoats, resistant to UV-induced delamination from topcoats)
IT Light stabilizers
(UV, cationic electrodeposition undercoats containing hindered amines and, resistant to UV-induced delamination from topcoats)
IT Amines, uses
RL: USES (Uses)
(hindered, cationic electrodeposition undercoats containing UV absorbers and, resistant to UV-induced delamination from topcoats)
IT 70321-86-7 104810-47-1 104810-48-2
RL: USES (Uses)
(UV absorber, cationic electrodeposition undercoats containing hindered amines and, resistant to UV-induced delamination from topcoats)
IT 63843-89-0 122586-52-1
RL: USES (Uses)
(cationic electrodeposition undercoats containing UV absorbers and, resistant to UV-induced delamination from topcoats)

L31 ANSWER 28 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1992:265242 HCAPLUS Full-text
DOCUMENT NUMBER: 116:265242
ORIGINAL REFERENCE NO.: 116:44799a,44802a
TITLE: Voltage-activated opaque-transparent-changing sheet materials
INVENTOR(S): Matsuda, Minoru; Yamakido, Masayoshi; Ito, Hidemi; Iwata, Koichi; Nakagawa, Sumihito
PATENT ASSIGNEE(S): Takiron Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

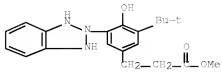
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 03255423	A	19911114	JP 1990-339056	1990 1130
PRIORITY APPLN. INFO.:			JP 1990-5368 A1	1990 0112
			JP 1990-21850 A1	1990 0130

ED Entered STN: 27 Jun 1992
AB The material comprises (1) a 1st transparent electrode, (2) a liquid crystal dispersed in a cured epoxy resin, (3) a 2nd transparent electrode. Optionally, the liquid crystal contains a UV absorber and/or a radical-capturing compound; a resin layer containing a UV absorber is formed between (1) and (2) and/or (2) and (3); the liquid crystal consists of a derivative of salicylate, benzophenone, benzotriazole, benzoate, hydroquinone, cyanoacrylate, thiodipropionic acid, hindered phenol, hindered amine; and the epoxy is cured using trimethylolpropane-tris-(β-thiopropionate) as a hardener. The material exhibits a reversible transparent-opaque change by on-off of the applied voltage and is suited for use in blinds, partitions, windows, and domes.
IT 141655-67-6
RL: USES (Uses)
(liquid crystal, voltage-activated light-shading sheet containing)
RN 141655-67-6 HCAPLUS

CN Benzenepropanoic acid, 3-(1,3-dihydro-2H-benzotriazol-2-yl)-5-(1,1-dimethylethyl)-4-hydroxy-, methyl ester, polymer with 1,2-ethanediol (9CI) (CA INDEX NAME)

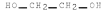
CM 1

CRN 141655-66-5
CMF C20 H25 N3 O3



CM 2

CRN 107-21-1
CMF C2 H6 O2



IC ICM G02F001-1333
ICS C09K019-54; E06B009-24; G02F001-137
CC 73-12 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
IT 82151-62-0, E 43 (Liquid crystal) 141655-67-6
RL: USES (Uses)
(liquid crystal, voltage-activated light-shading sheet containing)

L31 ANSWER 29 OF 29 HCAPLUS COPYRIGHT 2009 ACS on STN
ACCESSION NUMBER: 1977:509437 HCAPLUS Full-text
DOCUMENT NUMBER: 87:109437
ORIGINAL REFERENCE NO.: 87:17287a,17290a
TITLE: Light-sensitive material for positively active photovarnish used in manufacturing printing plates
INVENTOR(S): Wallbillich, Guenter; Saenger, Dietrich; Bronstert, Bernd
PATENT ASSIGNEE(S): BASF A.-G., Fed. Rep. Ger.
SOURCE: Ger. Offen., 16 pp.
CODEN: GWXXBX
DOCUMENT TYPE: Patent
LANGUAGE: German
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 2545957	A1	19770421	DE 1975-2545957	1975 1014
			<--	
PRIORITY APPLN. INFO.:			DE 1975-2545957	1975 1014

<--

ED Entered STN: 12 May 1984

AB Pos.-working quinone diazide type photoresists with improved light sensitivity are prepared Thus, 2,2',4,4'-tetrahydroxybenzophenone monoacetate 1 part dissolved in dioxane 10 parts was treated with 2 equivalent o-quinonediazidesulfonyl chloride. At 30°, a 1.5 molar excess Et3N was slowly added, and after 2 h the solution was filtered and poured into excess H2O and the yellow diazo compound (I) was collected. Then 70 parts I in 270 parts dioxane was treated with 210 parts Bisphenol A, 30 parts paraformaldehyde, and 4 parts p-toluenesulfonic acid. The reaction mixture was heated for 60 min at 60° and poured into a 4-fold excess MeOH containing 0.95 parts NaOH. A light-sensitive phenolic resin (II) with a mol. weight of 1880 was precipitated with H2O and collected. A solution containing II 200, Fanal blue B (C.I. 42595:2) 0.1% and EtCOMe-dioxane (3:1) 1800 was coated on a clean anodized Al plate. After drying the plate was exposed for 45 s with a 8000 W pulsed Xe lamp at 135-cm distance. The plate was developed in a 5% Na3PO4 solution for 30 s, followed by a H2O rinse and a dip in 1% H3PO4. After rinsing and drying the plate was used on a press to give 75,000 clean sharp prints.

IT 63956-53-6
RL: USES (Uses)
(photosensitive compns. containing, for lithog. plates)

RN 63956-53-6 HCAPLUS

CN 1-Naphthalenesulfonic acid, 6-diazo-5,6-dihydro-5-oxo-, monoester with 4-(2H-benzotriazol-2-yl)-1,3-benzenediol, polymer with formaldehyde and 4-methylphenol (9CI) (CA INDEX NAME)

CM 1

CRN 106-44-5
CMF C7 H8 O

CM 2

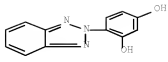
CRN 50-00-0
CMF C H2 O

CM 3

CRN 63956-52-5
CMF C22 H13 N5 O5 S
CCI IDS

CM 4

CRN 22607-31-4
CMF C12 H9 N3 O2



CM 5

CRN 20546-03-6
CMF C10 H6 N2 O4 S

IC G03F007-10
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic Processes)
IT 63956-50-3 63956-53-6 63956-54-7
RL: USES (Uses)
(photosensitive compns. containing, for lithog. plates)

FULL SEARCH HISTORY

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     (FILE 'HOME' ENTERED AT 13:38:10 ON 18 MAY 2009)

     FILE 'HCAPLUS' ENTERED AT 13:38:17 ON 18 MAY 2009
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L1             1 SEA SPE=ON  ABB=ON  PLU=ON  US20070043204/PN
                SEL RN

     FILE 'REGISTRY' ENTERED AT 13:39:02 ON 18 MAY 2009
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                794518-81-3/BI OR 794518-84-6/BI OR 95-14-7/BI)
                E N3C2/ES

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L3             STR

     FILE 'REGISTRY' ENTERED AT 13:42:41 ON 18 MAY 2009
L4             SCR 2043
L5            50 SEA SSS SAM L3 AND L4
L6          2975 SEA SSS FUL L3 AND L4
               SAV TEMP L6 FAN775REG/A
L7             3 SEA SPE=ON  ABB=ON  PLU=ON  L2 AND L6

     FILE 'HCAPLUS' ENTERED AT 13:44:57 ON 18 MAY 2009
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L10      1225078 SEA SPE=ON  ABB=ON  PLU=ON  OPTIC?
L11         153 SEA SPE=ON  ABB=ON  PLU=ON  L9 AND L10
L12             QUE SPE=ON  ABB=ON  PLU=ON  DEVICE? OR CONTRIVANCE? OR
                INVENTION? OR APPARAT? OR APP## OR IMPLEMENT? OR
                INSTRUMENT? OR TOOL? OR UTENSIL? OR EQUIP?
L13      149242 SEA SPE=ON  ABB=ON  PLU=ON  L10(2A)L12
L14         41 SEA SPE=ON  ABB=ON  PLU=ON  L13 AND L11
                D SCA L1
L15          86 SEA SPE=ON  ABB=ON  PLU=ON  L9 AND ?LUMIN?
L16           7 SEA SPE=ON  ABB=ON  PLU=ON  L14 AND L15
L17        1254 SEA SPE=ON  ABB=ON  PLU=ON  (ANOD? OR CATHOD?)(2A)(REFL
                ECT? OR TRANSMIS?)
L18           0 SEA SPE=ON  ABB=ON  PLU=ON  L9 AND L17
L19          57 SEA SPE=ON  ABB=ON  PLU=ON  L9 AND (REFLECT? OR
                TRANSMIS?)
L20          18 SEA SPE=ON  ABB=ON  PLU=ON  L9 AND (ANOD? OR CATHOD?
                OR ELECTROD?)
L21           3 SEA SPE=ON  ABB=ON  PLU=ON  L19 AND L20
L22             QUE SPE=ON  ABB=ON  PLU=ON  (CHARG? OR HOLE#  OR
                ELECTRON# OR E)(2A)(TRANSPORT? OR MIGRAT? OR TRANSFER?
                OR MOVE# OR MOVING# OR MOVEMENT? OR CARR?)
L23           5 SEA SPE=ON  ABB=ON  PLU=ON  L9 AND L22
L24          28 SEA SPE=ON  ABB=ON  PLU=ON  L16 OR L20 OR L21 OR L23
L25             QUE SPE=ON  ABB=ON  PLU=ON  PY=<2004 NOT P/DT
L26             QUE SPE=ON  ABB=ON  PLU=ON  (PY=<2004 OR PRY=<2004 OR
                AY=<2004 OR MY=<2004 OR REVIEW/DT) AND P/DT
L27          24 SEA SPE=ON  ABB=ON  PLU=ON  L24 AND (L25 OR L26)
L28             QUE SPE=ON  ABB=ON  PLU=ON  PHOTOELECTR? OR PHOTO?(A)EL
                ECTR?
L29           7 SEA SPE=ON  ABB=ON  PLU=ON  L9 AND L28
L30           7 SEA SPE=ON  ABB=ON  PLU=ON  L29 AND (L25 OR L26)
L31          29 SEA SPE=ON  ABB=ON  PLU=ON  L27 OR L30
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                D L31 1-29 IBIB ED ABS HITSTR HITIND
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